

Microactuators and Sensors for Microfluidics and Lab on a Chip applications

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Slides 20-56 are contributed by Michael Ramsey (Oak Ridge)

General reference: Nanoelectromechanics in Engineering and Biology, by M. P. Hughes

Functional Elements

I/O

pipette
inkjet
electrospray

separations

electrophoretic
chromatographic
sizing
heterogeneous

filters

physical
polymeric
SPE

cytometry

immunoassay
staining
cell sorting

reactions

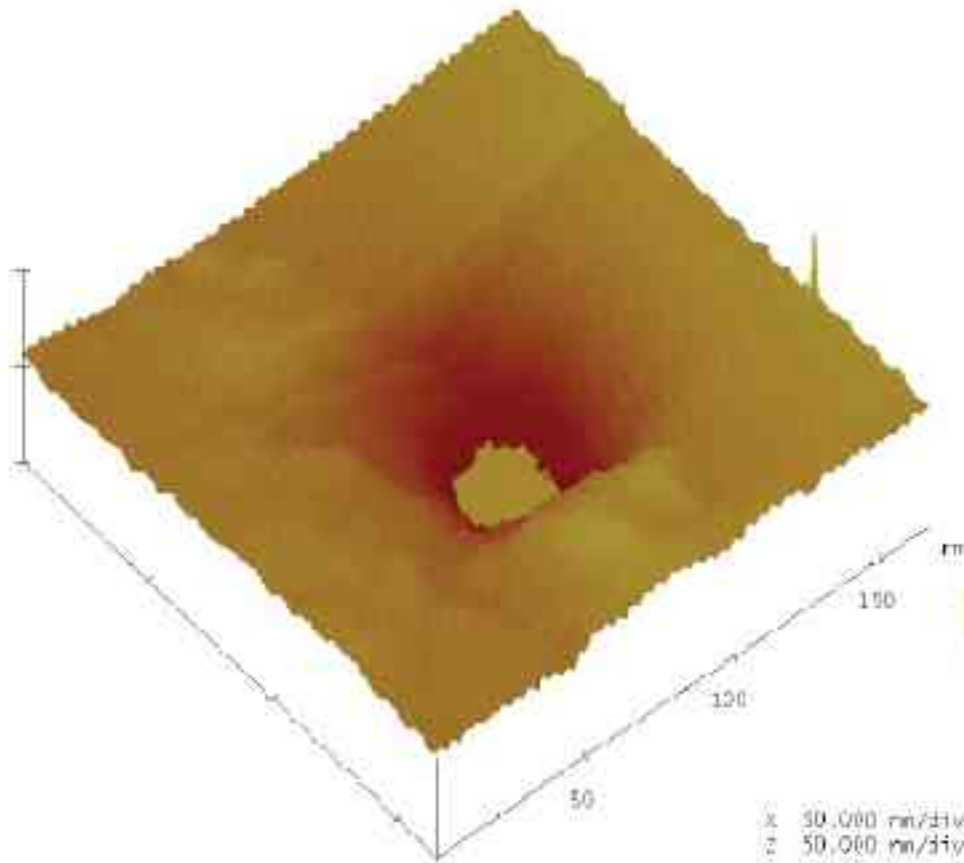
stopped flow
continuous flow
thermal cycling

detection

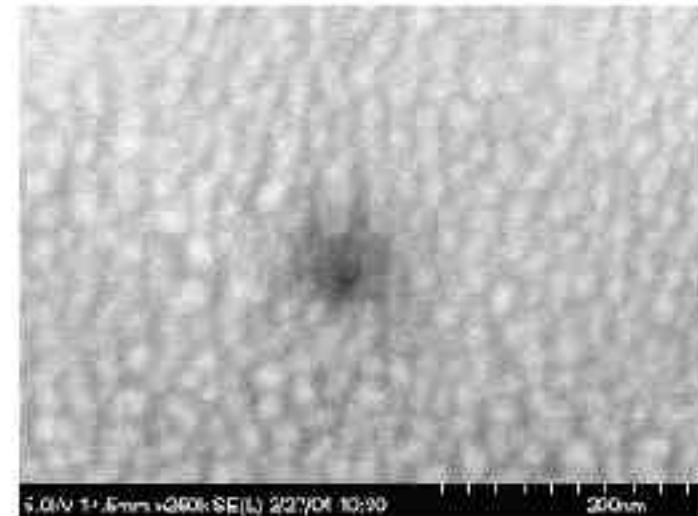
fluorescence
absorbance
refractive index
scattering
electrochemical
MS

FIB Milled Nanochannels in SiO₂ Membranes

- 40-nm thick SiO₂ membrane
- 500 μ S FIB dwell time, 70 pA
- AFM tip: $r = 40$ nm; $\theta_{1/2} = 35^\circ$
- Estimated diameter ≈ 50 nm

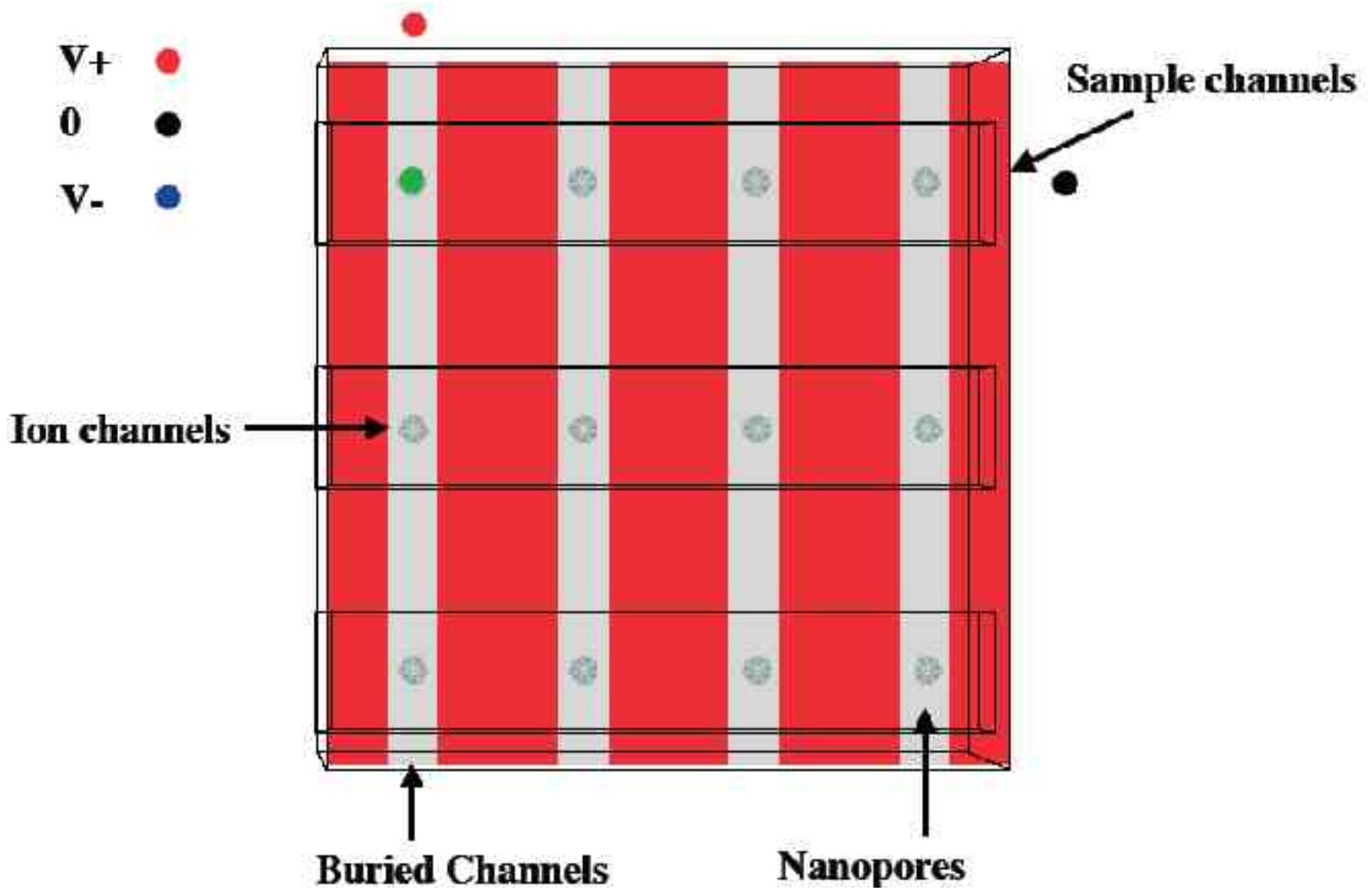


AFM Image



SEM Image


Addressable Ion Channel Arrays



Fundamental Questions

- **Can nanoscale channels be fabricated to molecular dimensions?**
- **What is the dimensional stability of a molecular scale channel?**
- **Can interfacial characteristics be sufficiently controlled**
- **What are the characteristics of fluid transport in molecular scale channels?**
- **How can such fluids/molecules be probed experimentally?** ←

Nanofluidics will be Enabling

- **Emulation and interface to biological systems**
 - **Artificial cells**
 - **Biological and chemical sensing**
- **Molecular characterization**
 - **Molecular counting**
 - **DNA sequencing**
 - **Protein and peptide sizing**
- **Fabrication (synthesis) of single molecules**
 - **Heterogeneous polymers**
 - **Complexes with controlled substitution**
- **Hardened (self-repairing) electronics**
 - **Fluidic-based molecular electronic gates**
 - **Molecular-based memories** 

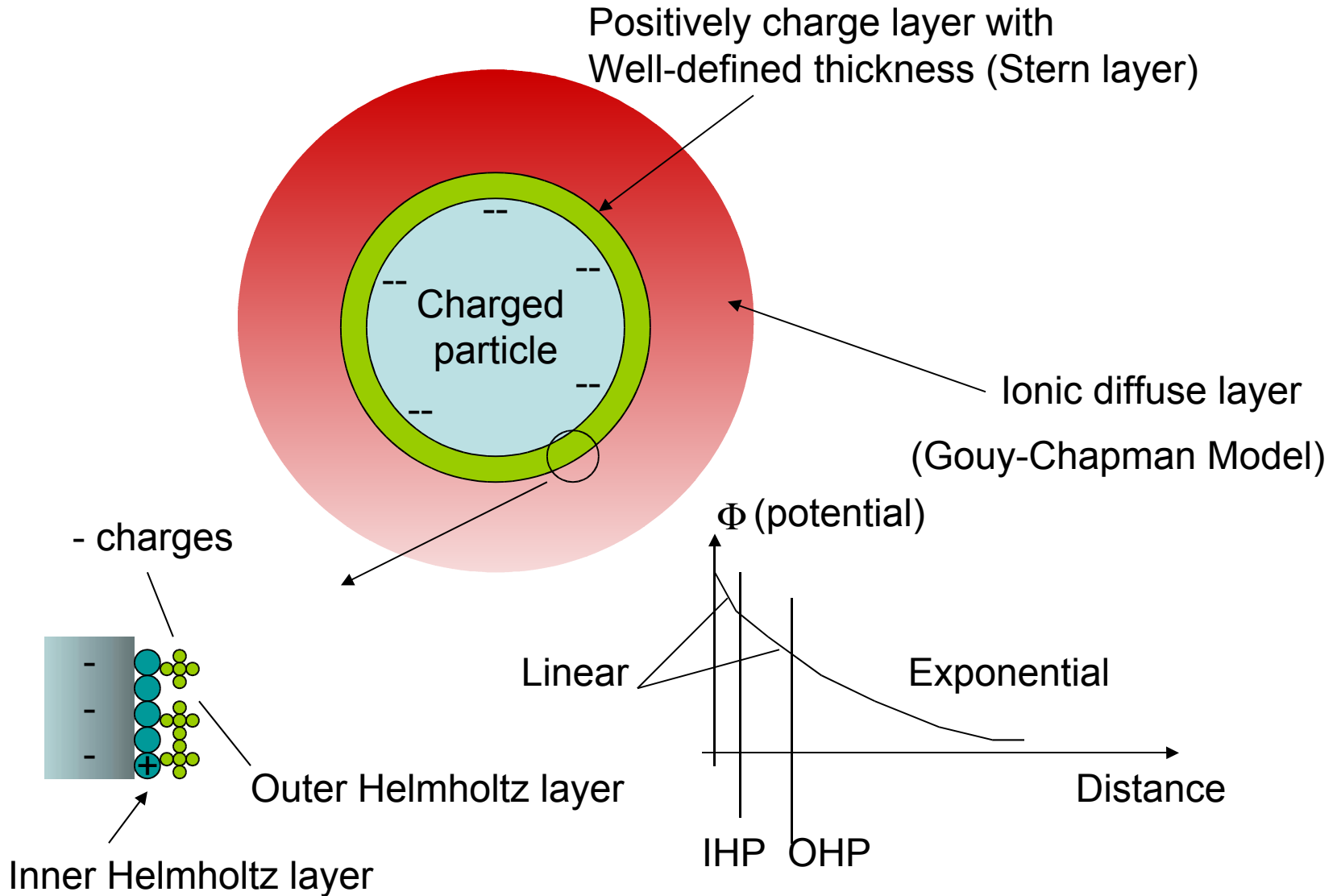
Needs

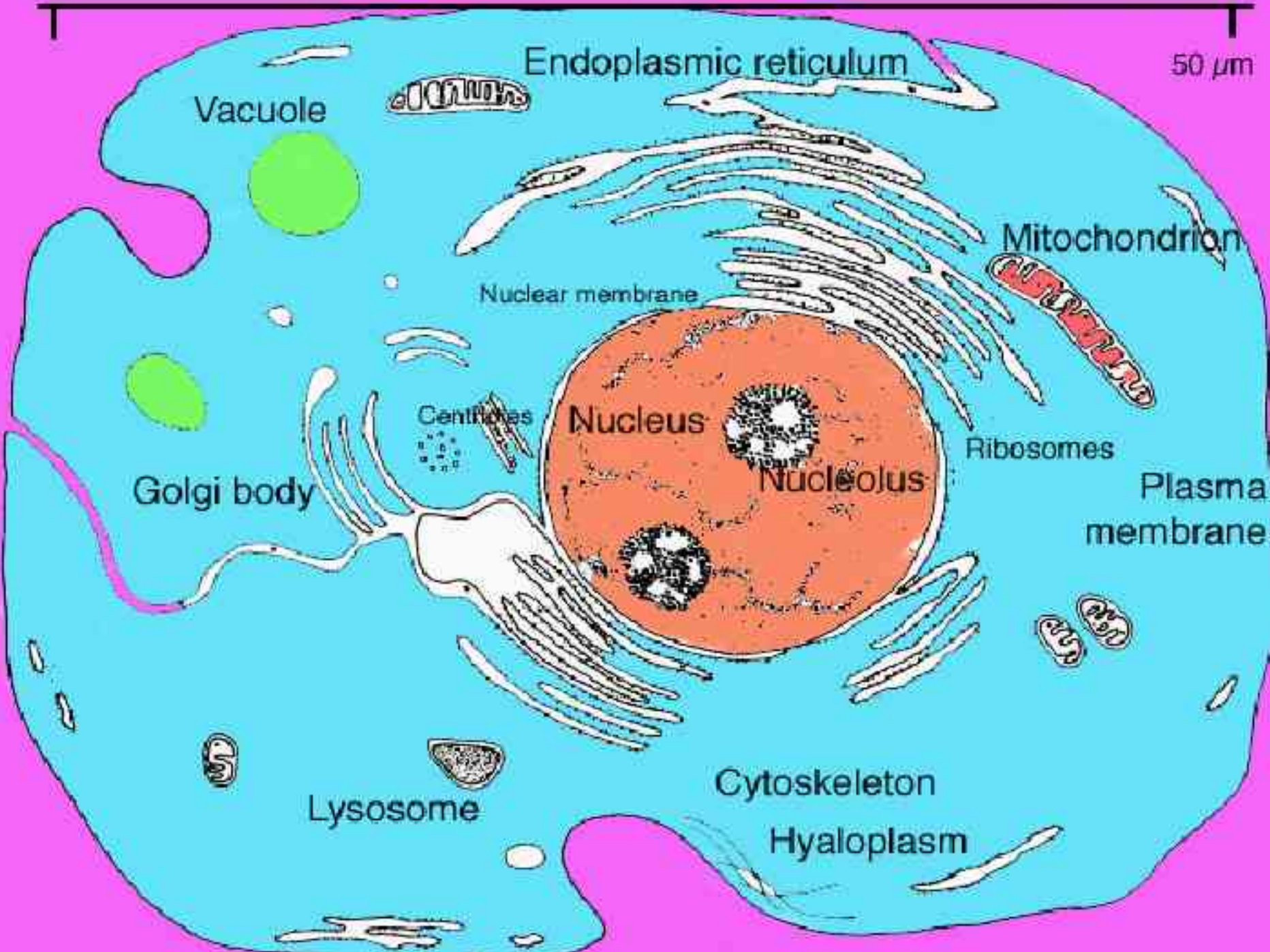
- **Materials**
 - Micro- and nanoscale fabrication
 - Interfacial chemistry
- **Nanoscale transport**
 - Fluids
 - Polymers
 - Experiment and simulation benchmarking
- **Sensors**
 - Integrated flow sensors
 - Integrated voltage sensors
 - Ultrasensitive analyte detectors
 - Non-selective
 - Selective

Future Directions

- **Biochemistry integrated with HP separations**
 - Single cell assays
 - Protein manipulations
- **Nanofluidics**
 - Low dimensional fluid transport
 - Molecular transport ($r_g > h$)
 - Single molecule manipulation, detection, and characterization
- **Chemical synthesis**
- **Handheld microfabricated mass spectrometers**

Electric Double Layer





Endoplasmic reticulum

50 μ m

Vacuole

Mitochondrion

Nuclear membrane

Nucleus

Ribosomes

Plasma membrane

Nucleolus

Golgi body

Centrioles

Cytoskeleton

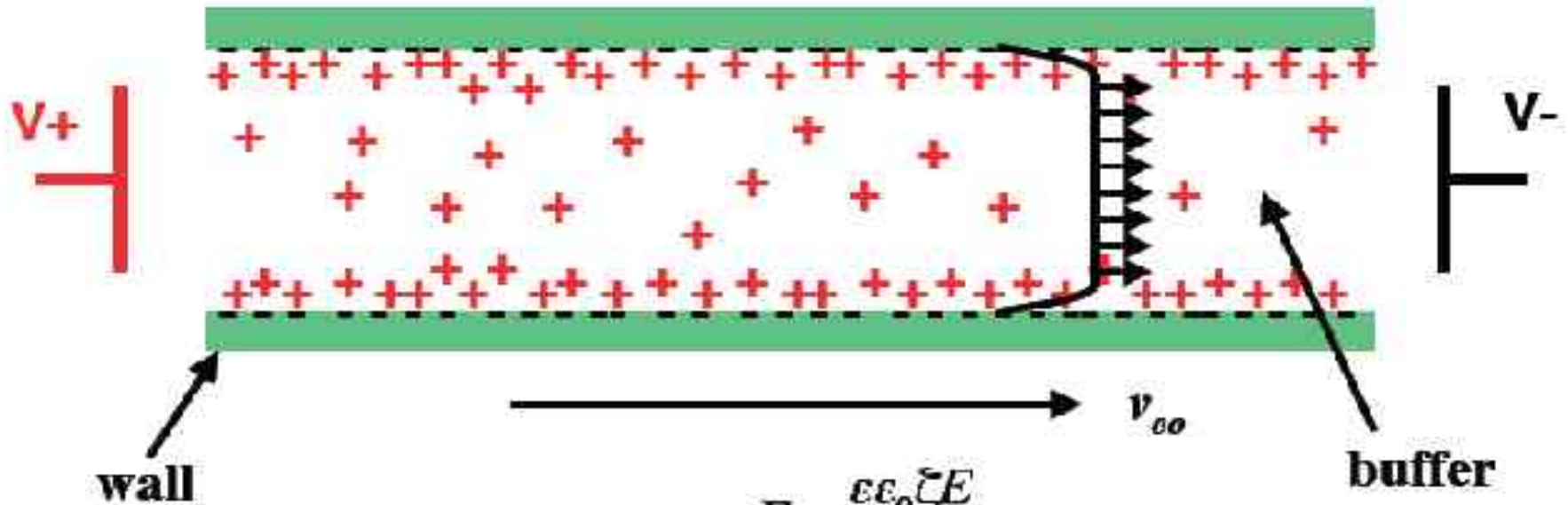
Lysosome

Hyaloplasm

Electrokinetic Forces

Force	AC or DC	Origin (Force)
Electrophoresis	DC	Caused by charge in E-field (QE)
Dielectrophoresis (DEP)	AC/DC	Caused by induced dipole in field gradient (Qd. ∇E)
Electro-osmosis	AC/DC	Caused by interaction between double layer charges and tangential E-field
Electrorotation	AC	Caused by dipole lag in rotating E-field (Torque=Dd X E)
Traveling wave DEP	AC	Caused by dipole lag in traveling E-field
Electro-orientation	AC/DC	Caused by interaction between dipole and electric field

Electrokinetic Transport



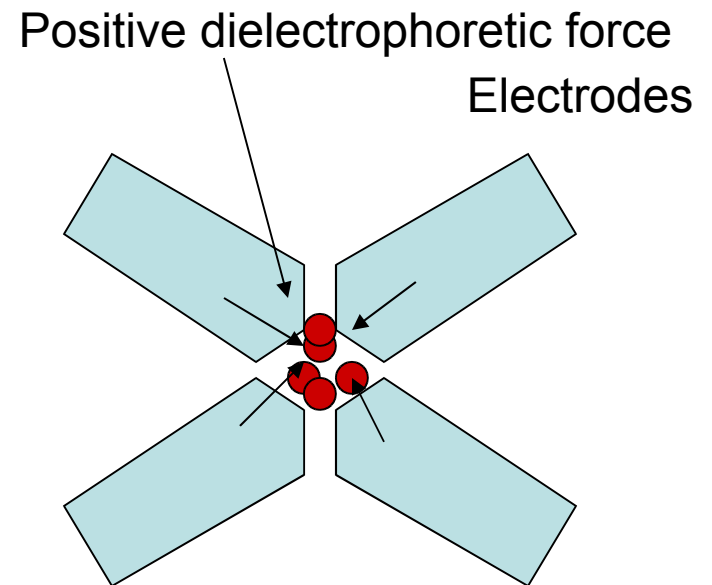
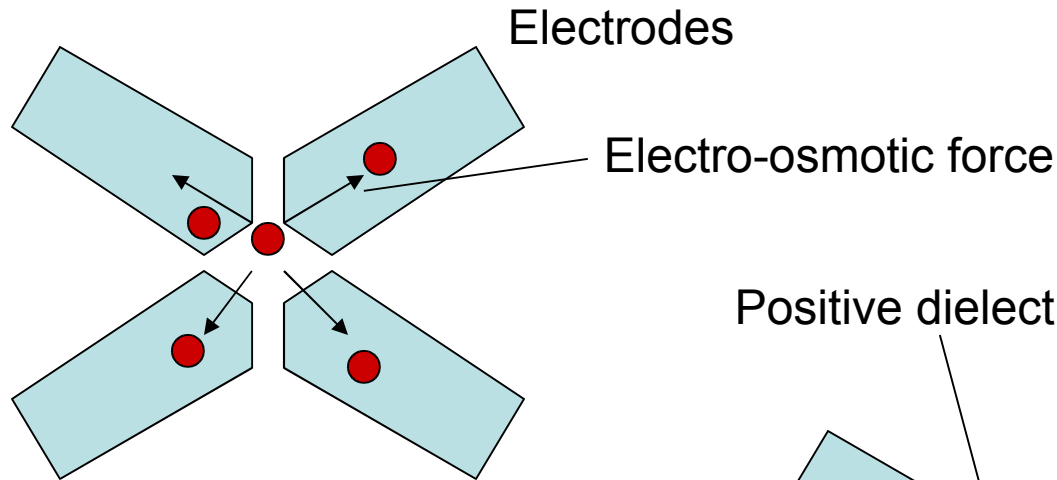
$$v_{eo} = \mu_{eo} E = \frac{\epsilon \epsilon_0 \zeta E}{4\pi r \eta}$$

$$v_{ep} = \mu_{ep} E = \frac{ezE}{6\pi r \eta}$$

$$v_{eff} = \mu_{eff} E = (\mu_{eo} + \mu_{ep}) E$$

eo: electroosmosis
 ep: electrophoresis
 η : viscosity

- Negative dielectrophoresis
- Positive dielectrophoresis
- Brownian motion, dielectrophoretic, and electro-osmotic balance



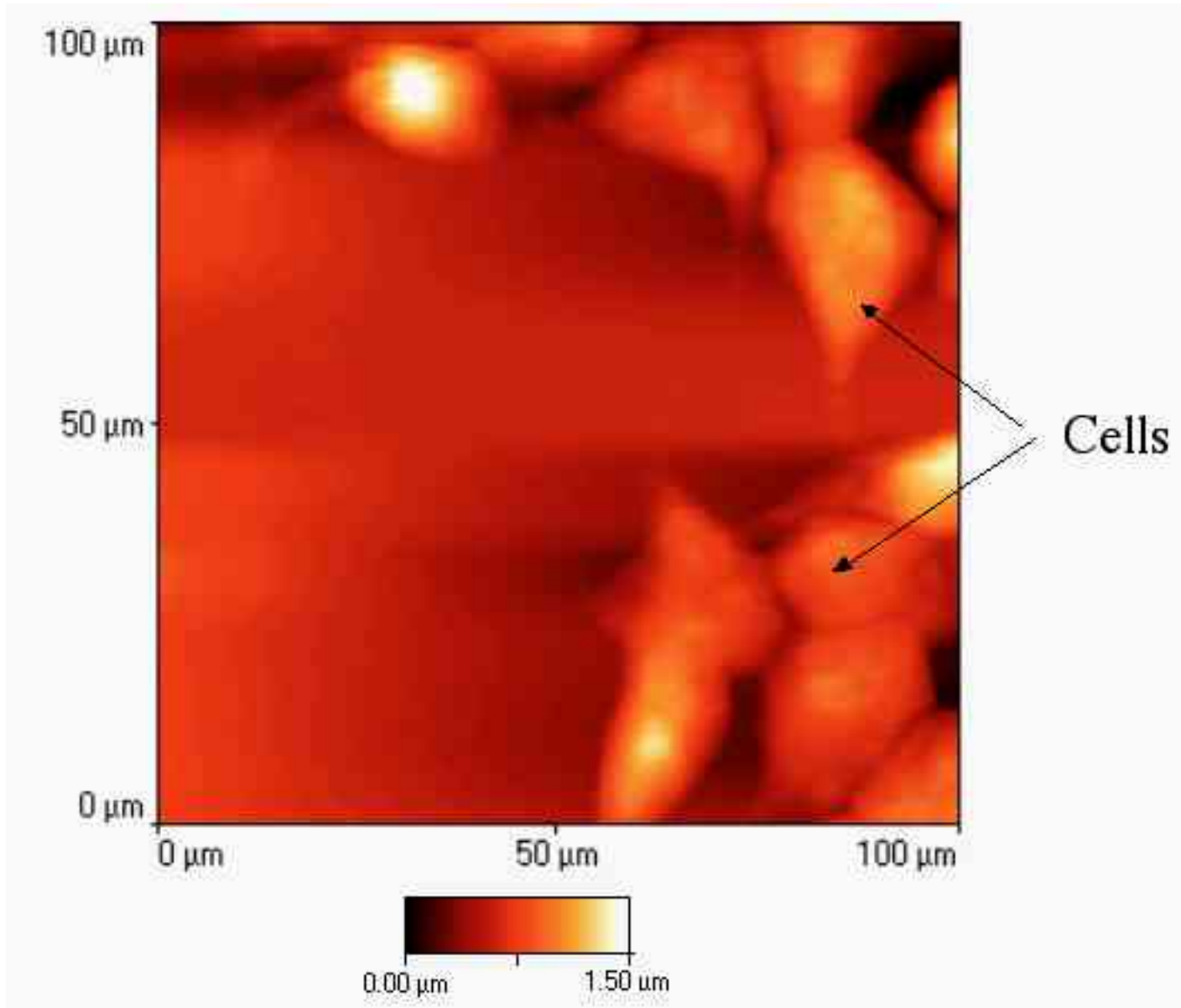
Negative dielectrophoretic force arises when ϵ_{real} becomes negative

Existing Tools

- Scanning local probe microscopy offers nearly atomic resolution:
 - Scanning tunneling microscopy (STM)~1Å
 - Atomic force microscopy (AFM)~ 10Å
 - AFM-related techniques >10Å
 - Magnetic force microscopy (MFM)
 - Scanning capacitance microscopy (SCM)
 - Near-field scanning optical microscopy (NSOM)~ 50Å



Atomic Force Microscopy (AFM) of Cells



Approach

Atomic Force Microscopy
(AFM)

Near-Field Scanning
Optical Microscope



Scanning Evanescent Microwave Probe (SEMP)

Non-ionizing

Sub-surface sensitive

Nearly atomic resolution

Challenging

Conductivity and permittivity information

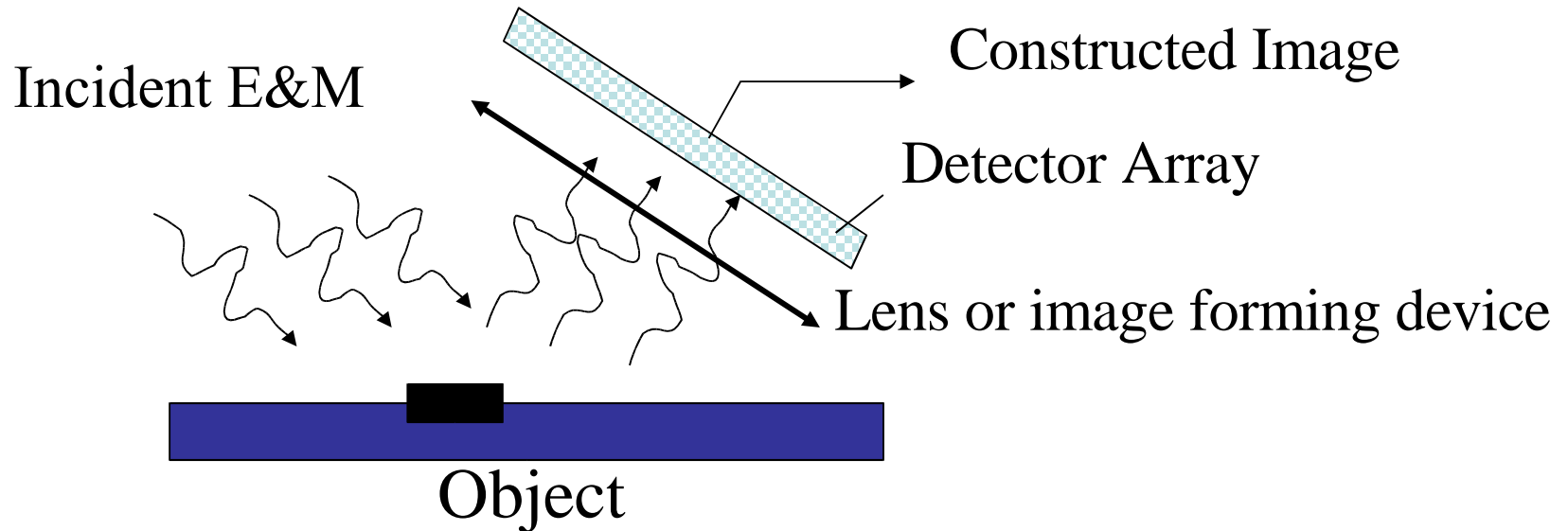
Compatible with AFM and NSOM

Hyperspectral

Components are commercially available

Non-contact and does not require conducting sample

Traveling wave imaging

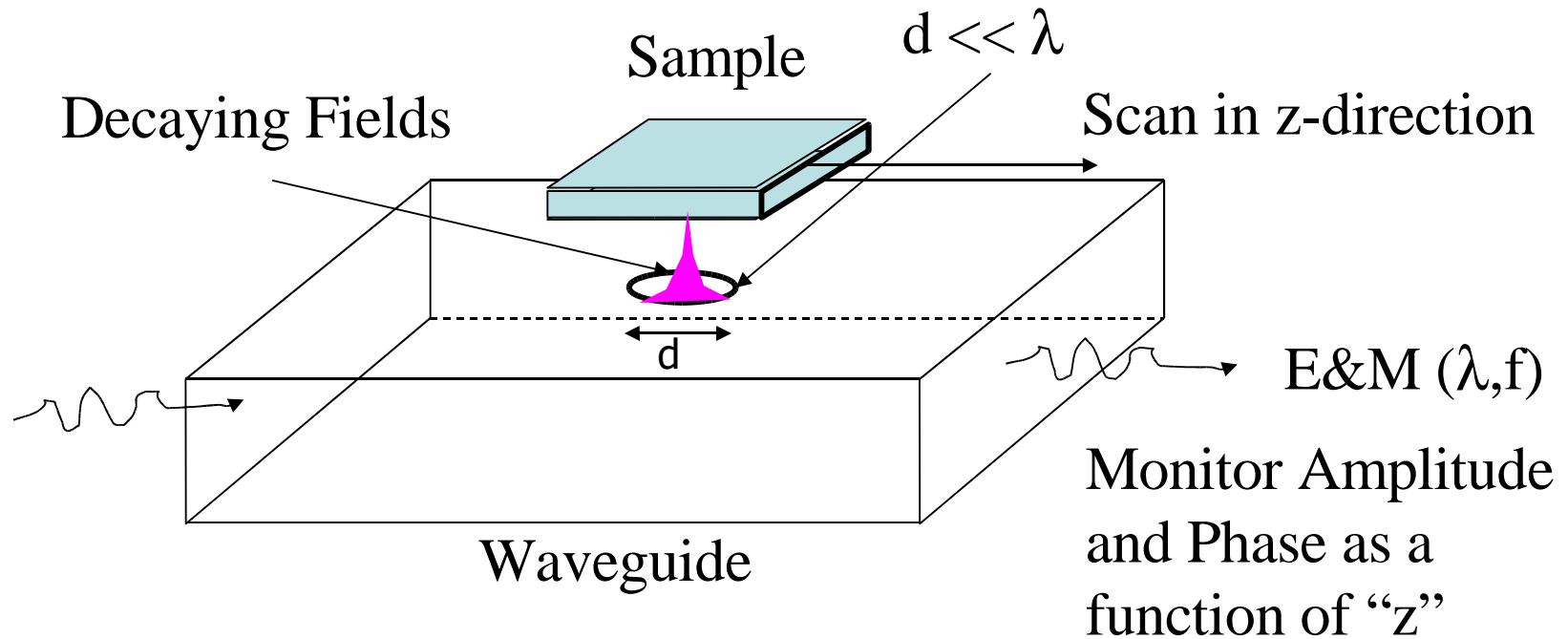


Resolution \sim Wavelength of incident E&M (λ)

Advantage: One shot imaging

E&M: electromagnetic wave

Decaying, or Evanescent Wave Imaging



Resolution $\sim d \ll \lambda$

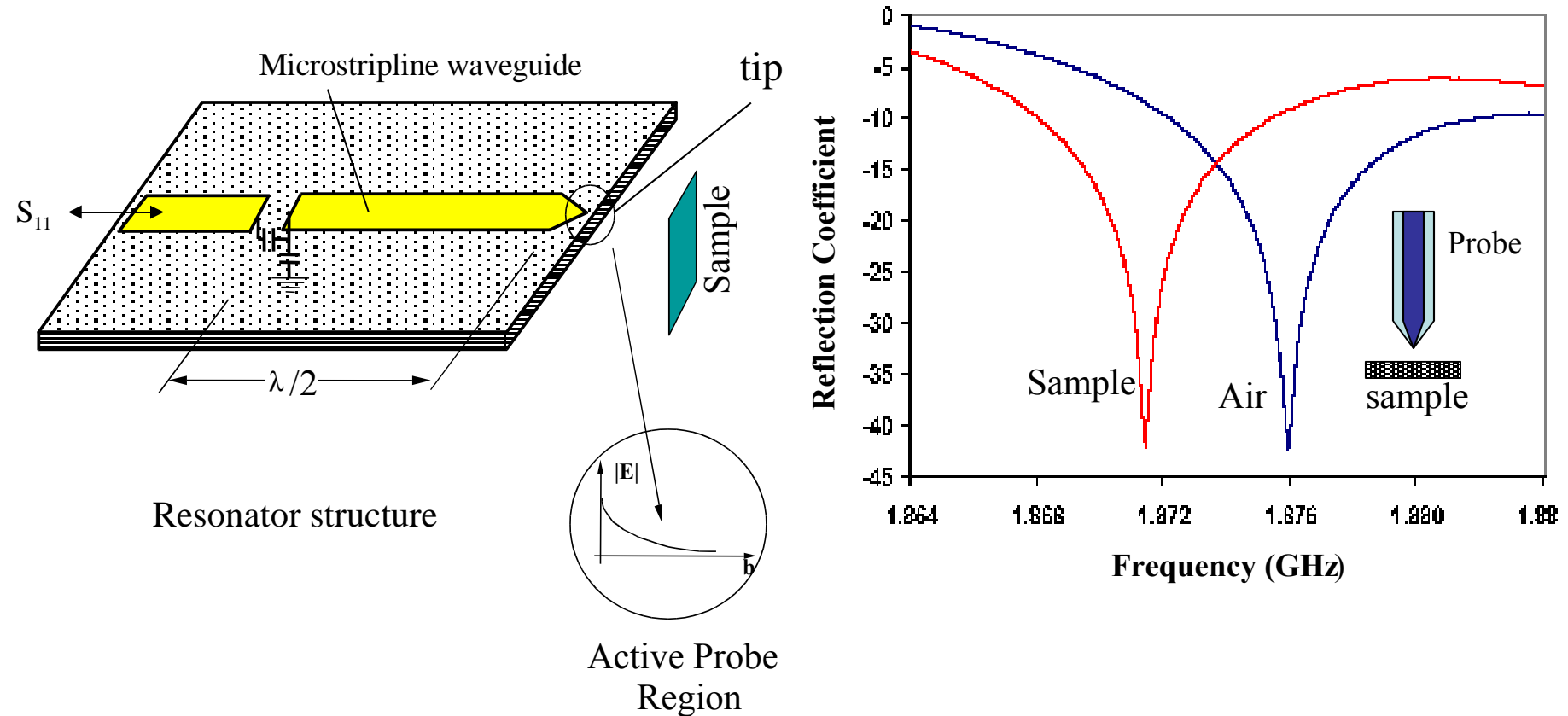
Disadvantage: Point by point imaging

λ : wavelength of E&M

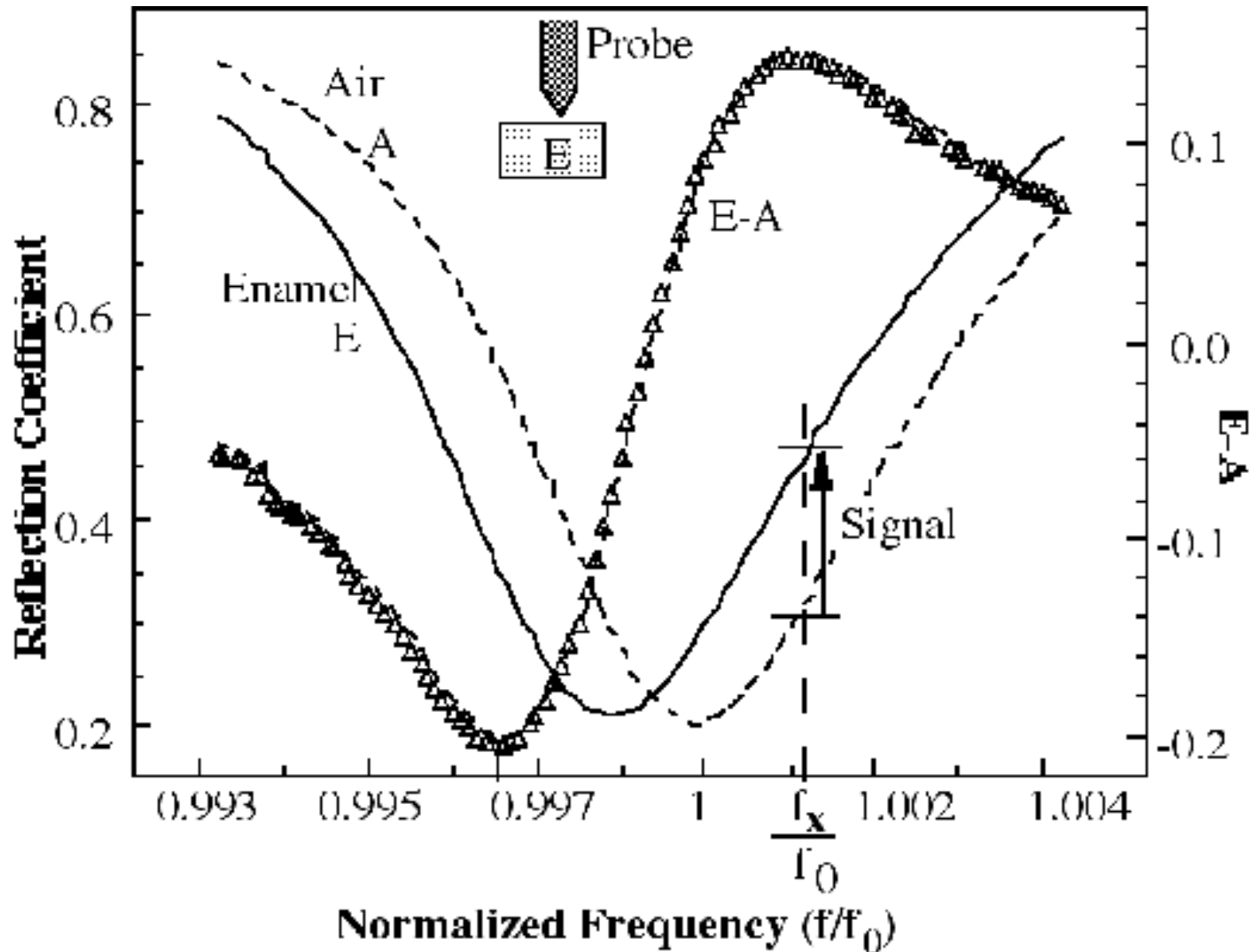
d : diameter of the waveguide opening

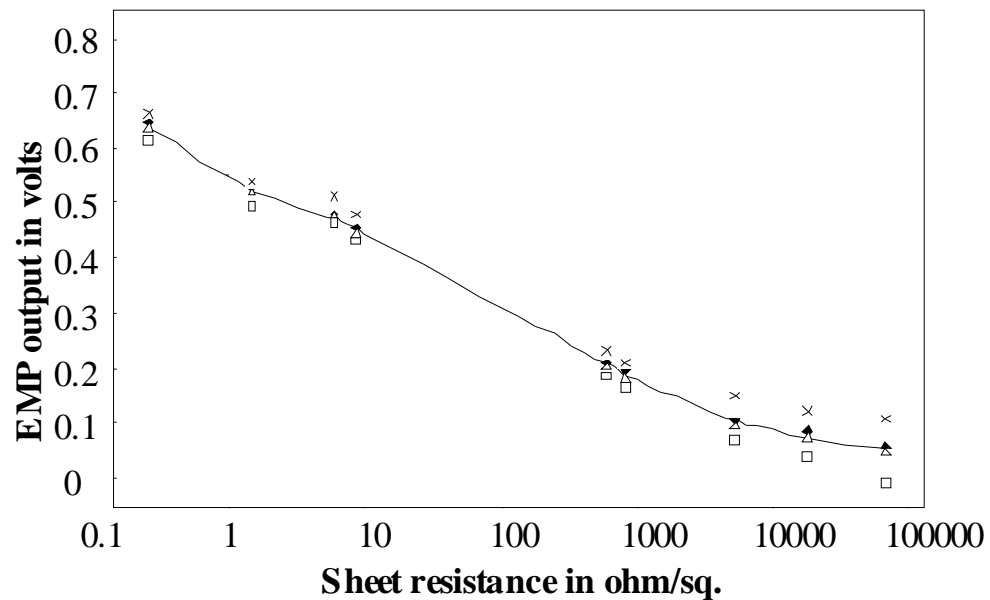
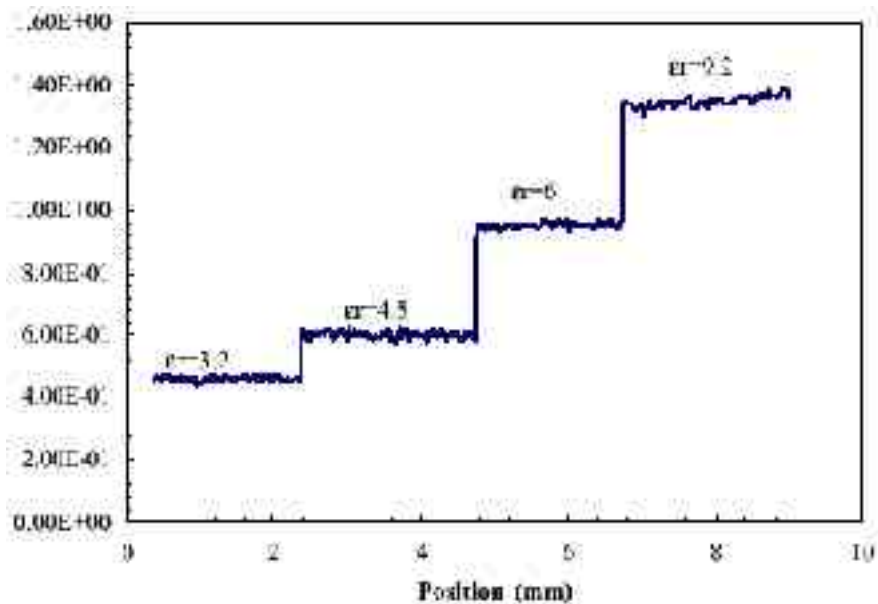
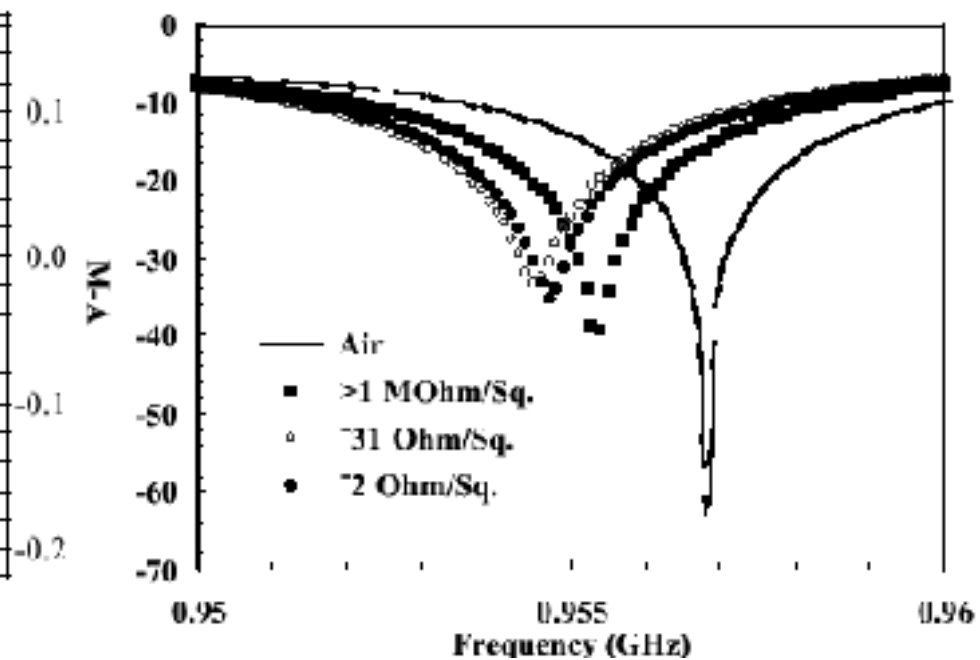
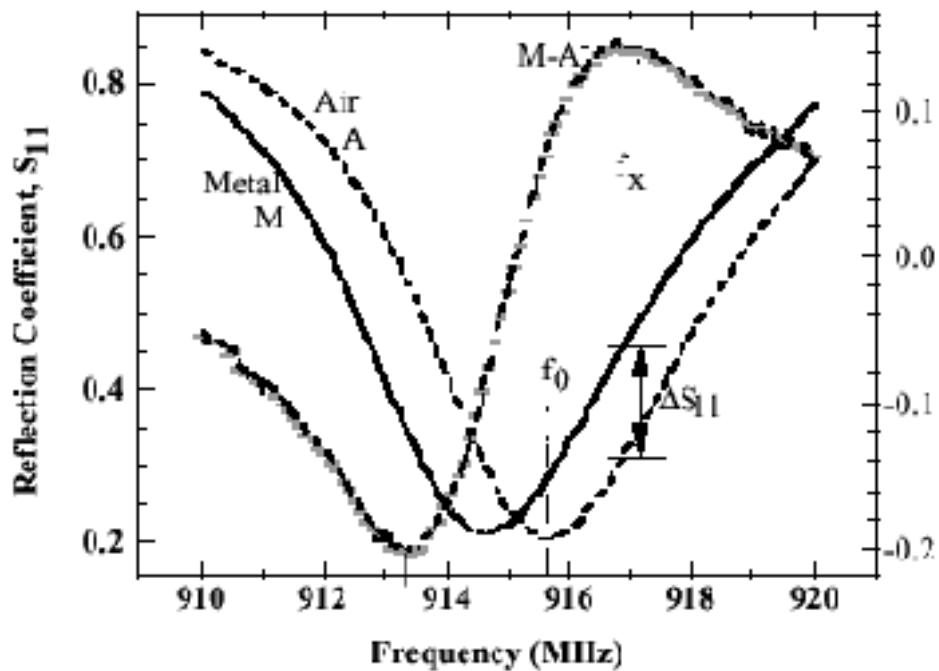
Scanning Evanescent Microwave Microscopy

- Evanescent fields are produced at the tip of a resonator
- Interaction between evanescent microwave field and sample
- Monitoring the resonance change of the probe resonator



S_{11} Spectra of Human Molar Enamel





Experimental Arrangement

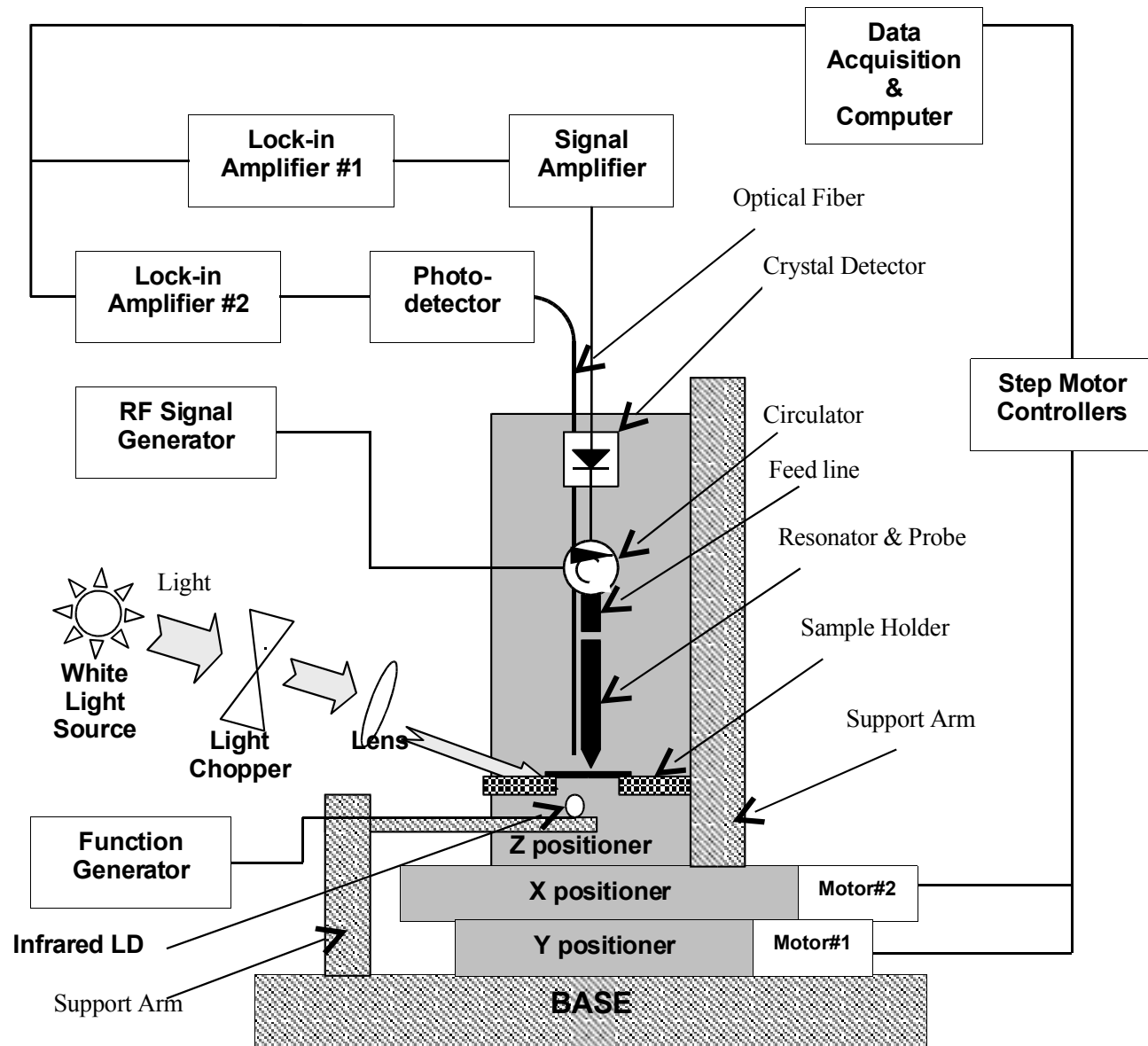
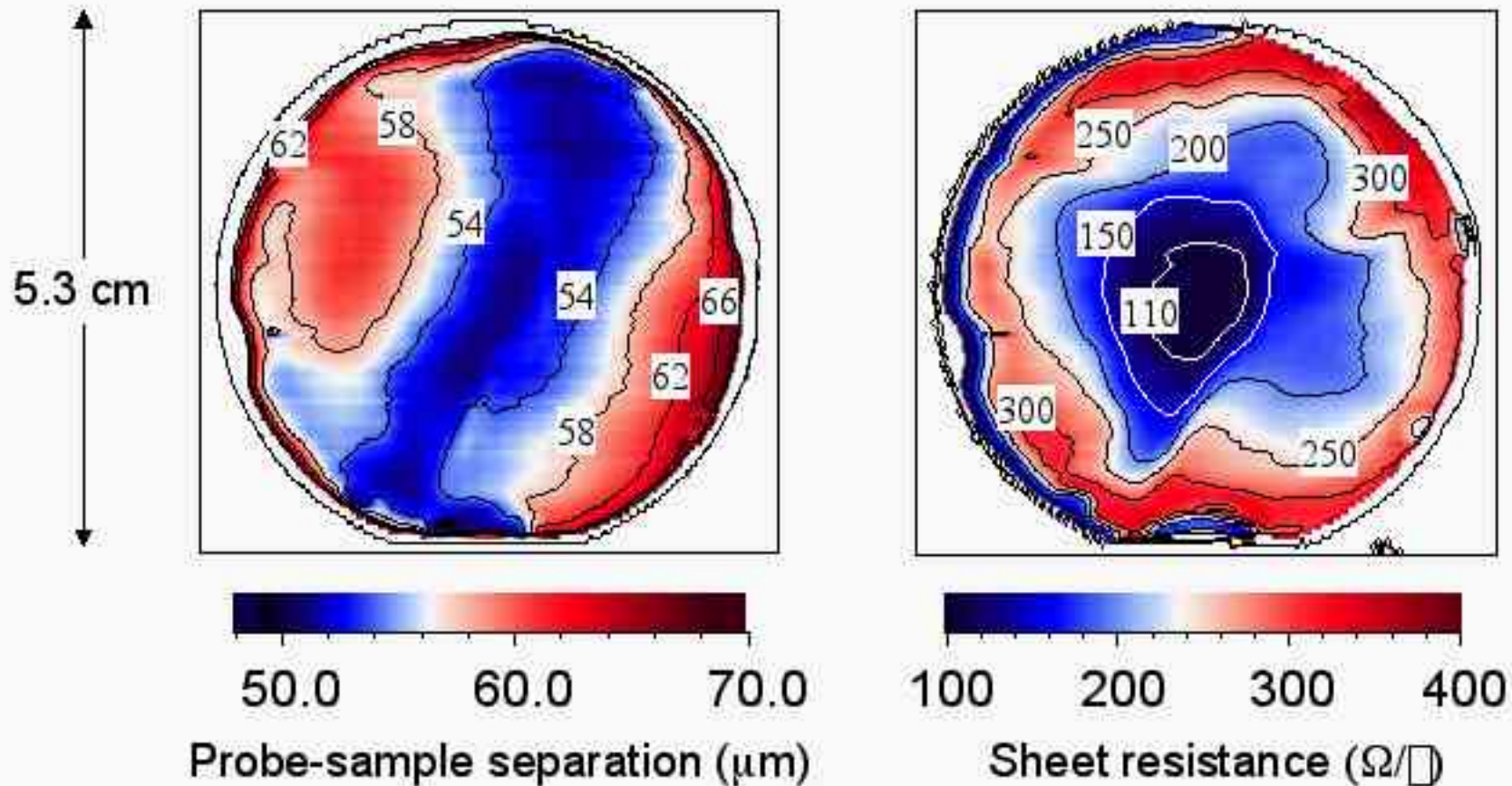


Fig. Schematic of the experimental setup

SEMP IMAGES: Topography & Sheet Resistance



Sample: $\text{YBa}_2\text{Cu}_3\text{O}_{7.8}$ thin film on 2" sapphire wafer

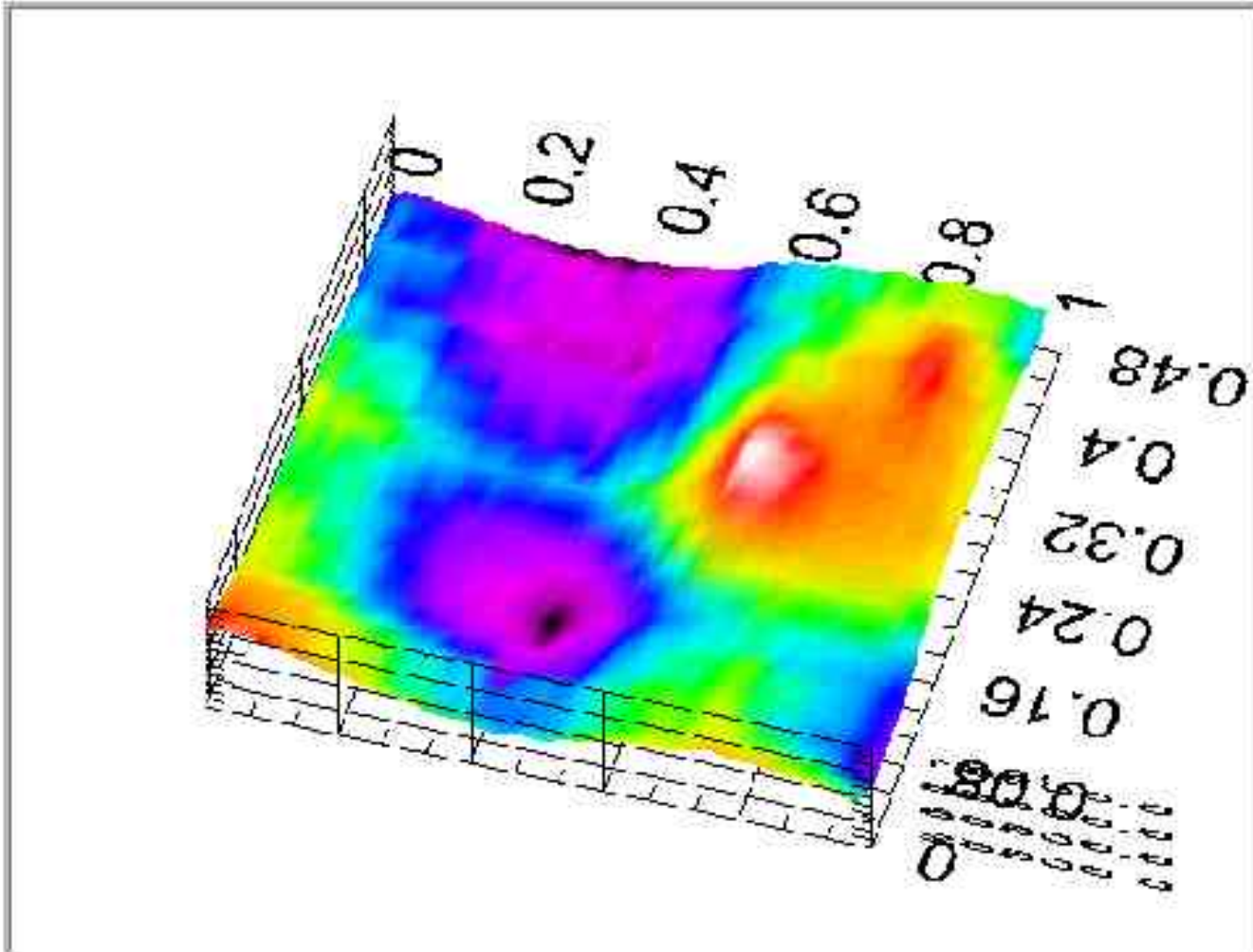
Frequency: 7.5 GHz

Temperature: 300 K

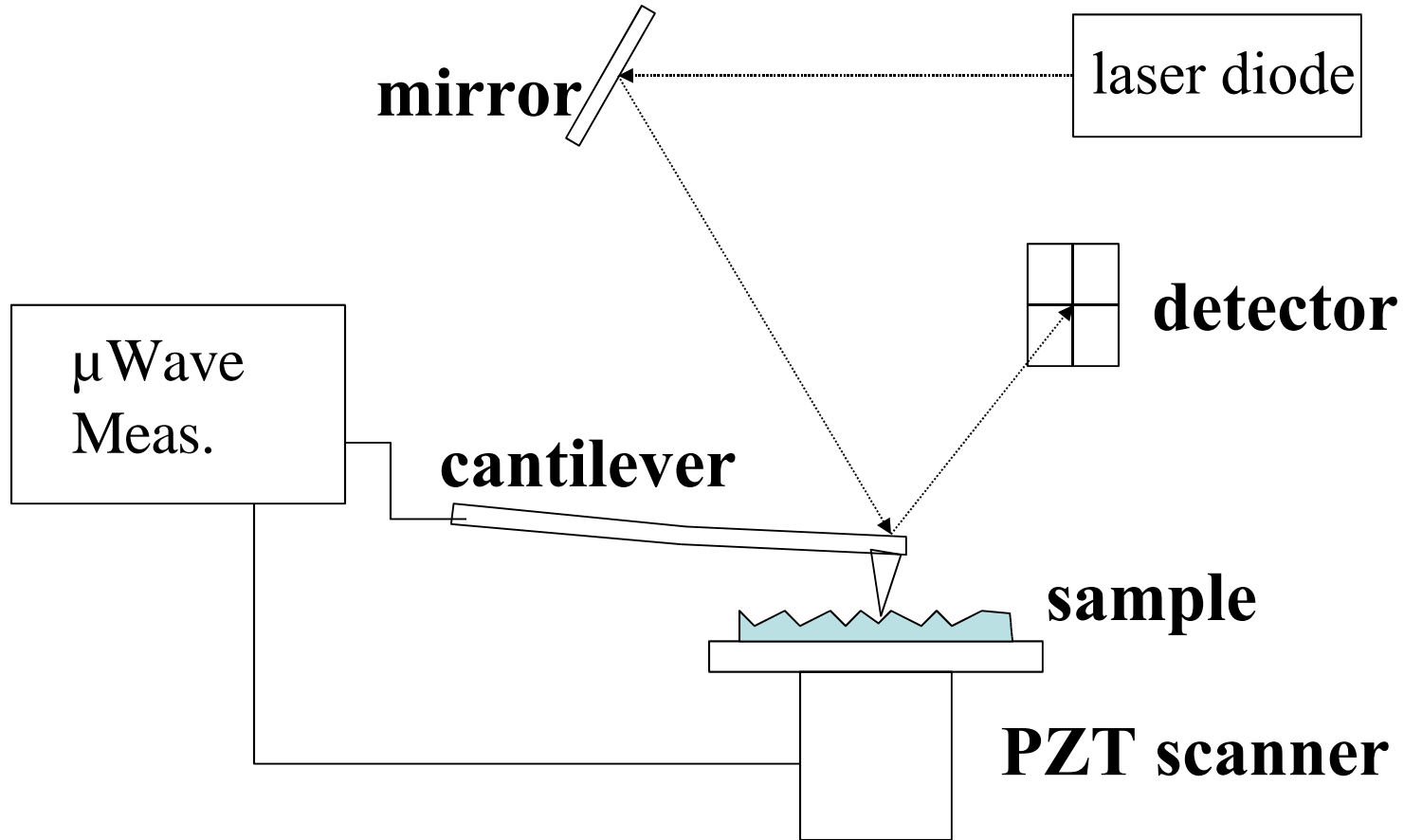
500 μm probe, in non-contact mode

Appl. Phys. Lett. **72**, 861 (1998)

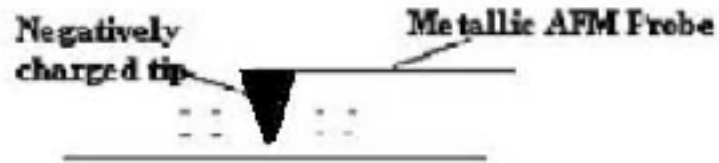
SEMP Image of Mold Release De-Bond with Two Bubbles in Epoxy



SEMP Integrated with AFM Setup



- Impedance spectroscopy (performed with an AFM) is used to image embedded structures in a material
- These embedded nanoparticles cannot be detected with traditional AFM topographical probing.
- A.C. signal applied between tip and sample results in a displacement current that is used to detect embedded structures.



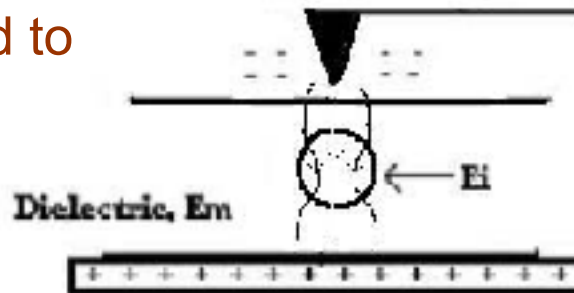
Dielectric, ϵ_m



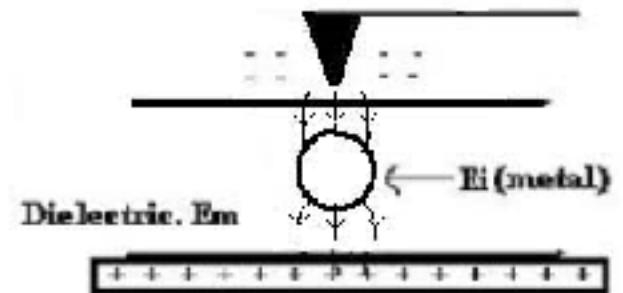
$$C = Q/V$$

Positively charged metallic plate

$\epsilon_i > \epsilon_m$

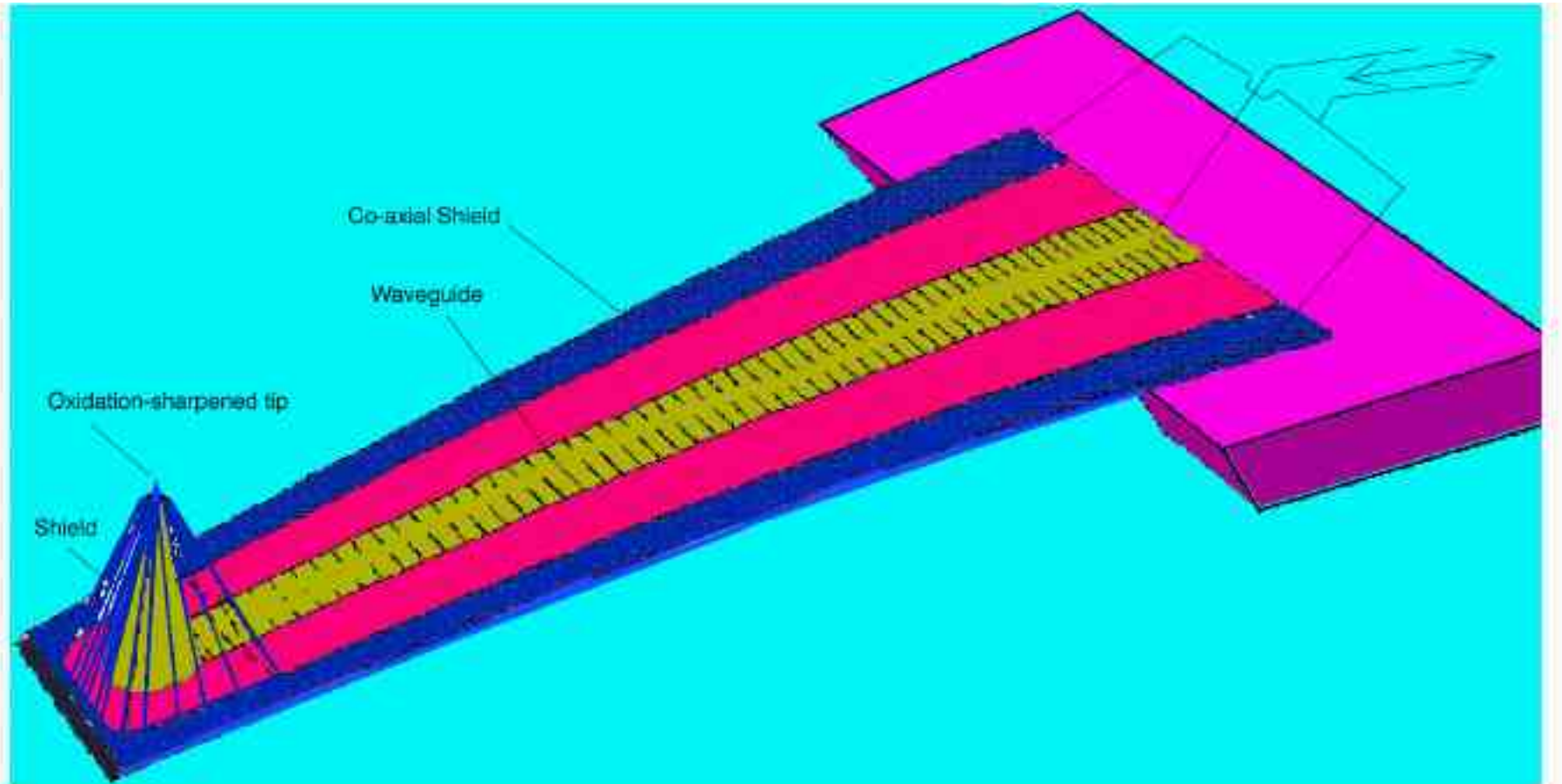


For $\epsilon_i < \epsilon_m$, the field bows outward for a dielectric embedded structure



Capacitance is highest for a metallic embedded structure

AFM-Compatible SEMP tip

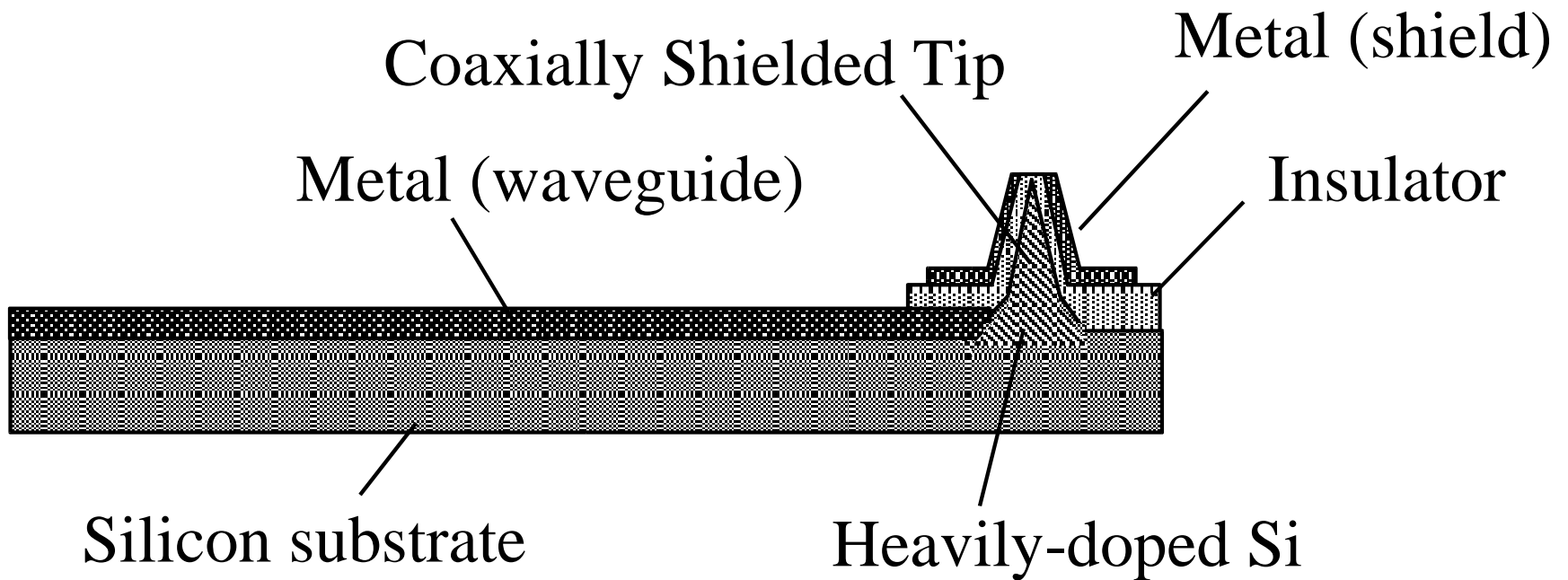


- No cutoff frequency with coaxial geometry
- Shielded to limit Coulomb interactions and increase electric-field resolution
- Orthogonal, simultaneous probing of topography/field

SEMP-AFM Combined Imaging



Probe Cross Section



Mechanical Design

$$E = \frac{E_{si}t_{si} + E_{LTO}t_{LTO} + E_{Al}t_{Al}}{t_{si} + t_{LTO} + t_{Al}}$$

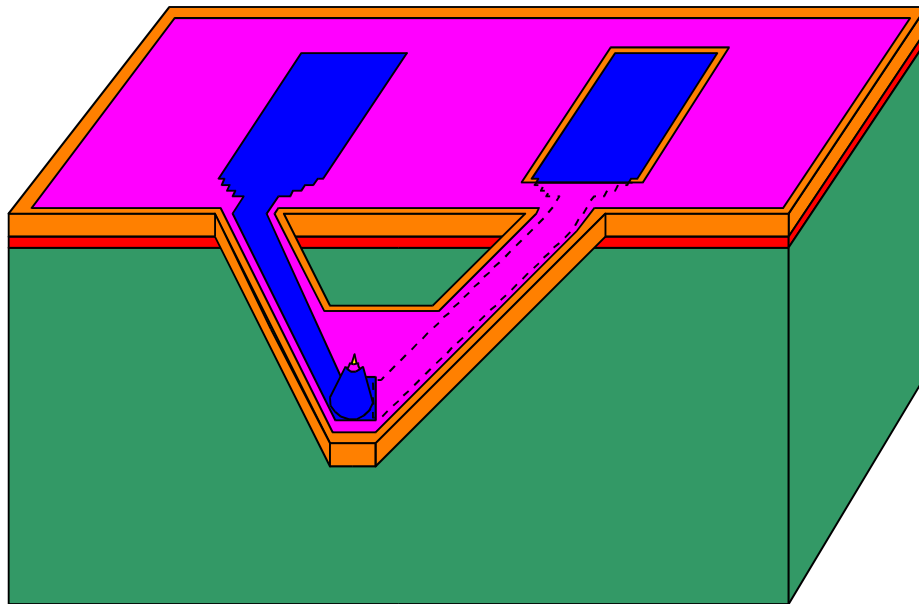
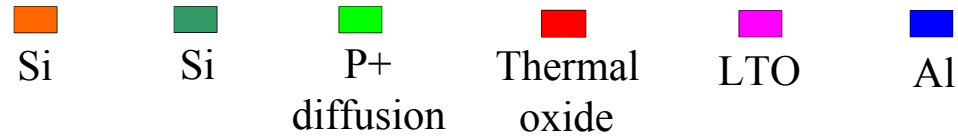
$$\rho = \frac{\rho_{si}t_{si} + \rho_{LTO}t_{LTO} + \rho_{Al}t_{Al}}{t_{si} + t_{LTO} + t_{Al}}$$

$$K = \frac{6EI}{L^3} = \frac{EW}{2} \left(\frac{t}{L} \right)^3$$

$$f_0 = \frac{3.52}{\pi} \frac{t}{L^2} \sqrt{\frac{E}{12\rho}}$$

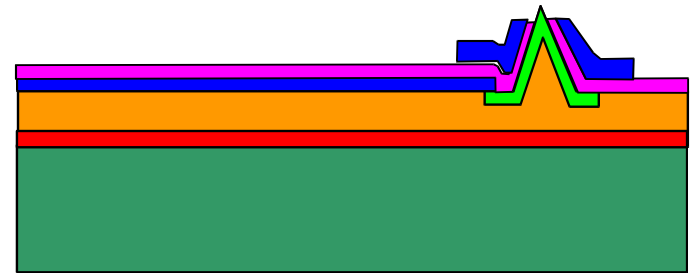
W = 50 μm	L = 300 μm		L = 450 μm		L = 1000 μm	
	t = 3 μm	t = 5 μm	t = 3 μm	t = 5 μm	t = 3 μm	t = 5 μm
Spring constant (N/m)	5.84	21.7	1.73	6.42	0.16	0.59
Resonant frequency (KHz)	95.5	150	42.5	66.5	8.60	13.5

Scanning Near-field Microwave Microscope Probe



(a)

Three dimensional view of an SNMM probe

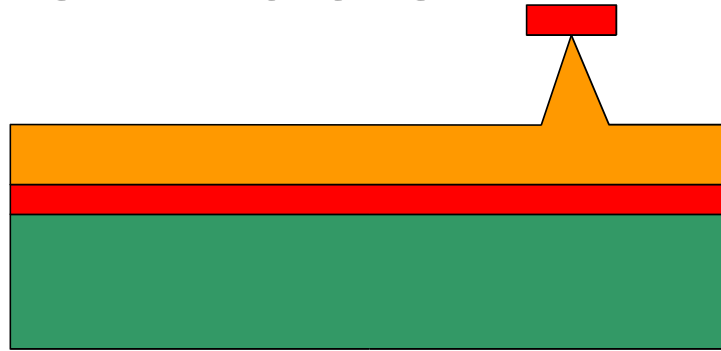


(b)

Cross-section view along a waveguide arm

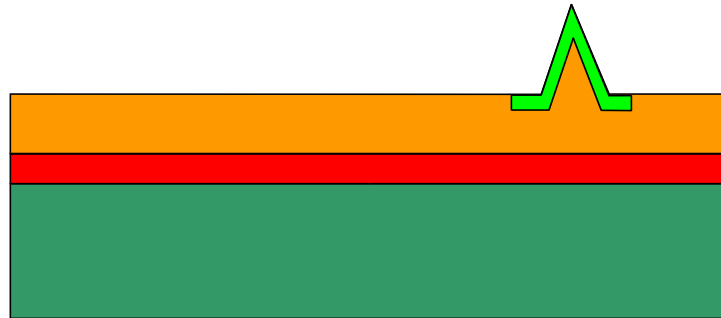
Microfabrication: Tip Formation

Thermal oxidation
Lithography
Oxide etching
Plasma etching tip



(a)

Oxidation sharpening
Lithography
Oxide etching
P+ ion implantation



(b)



Si



Si



P+ diffusion



Thermal oxide

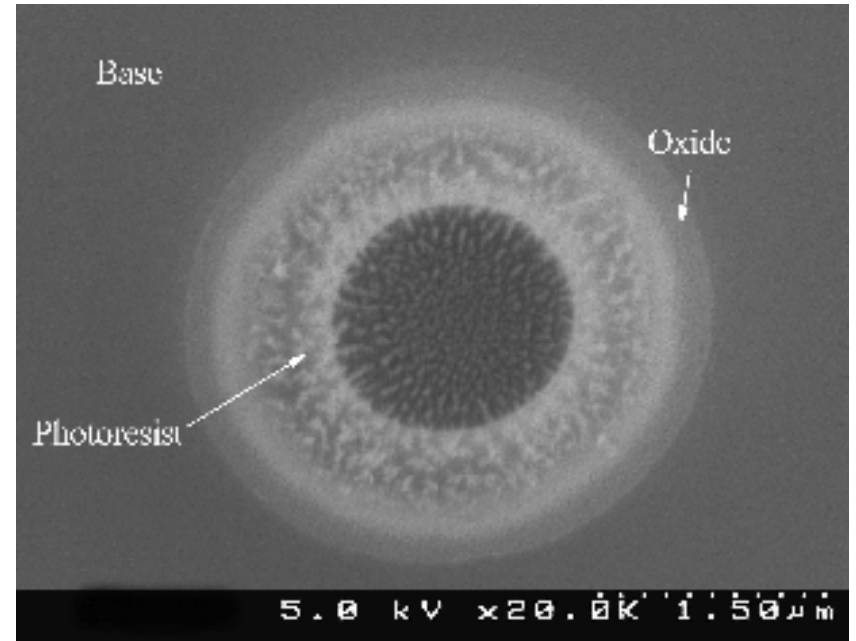
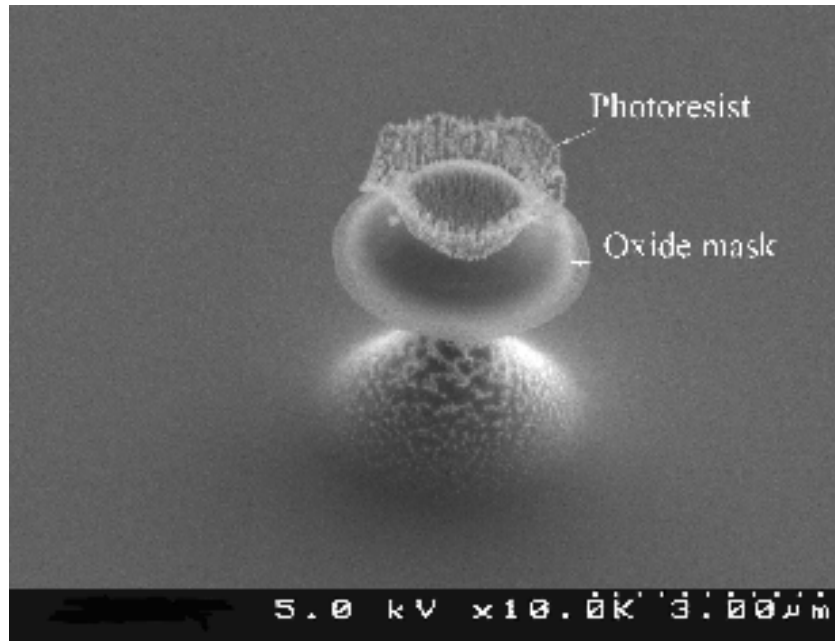


LTO

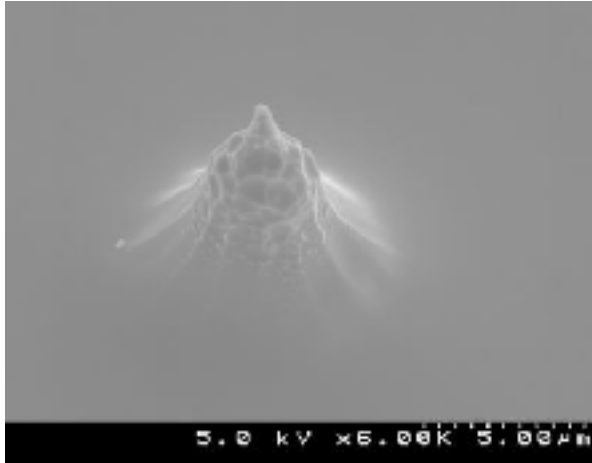


Al

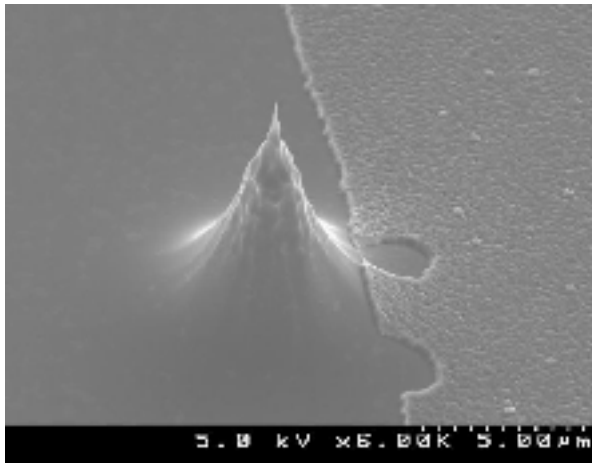
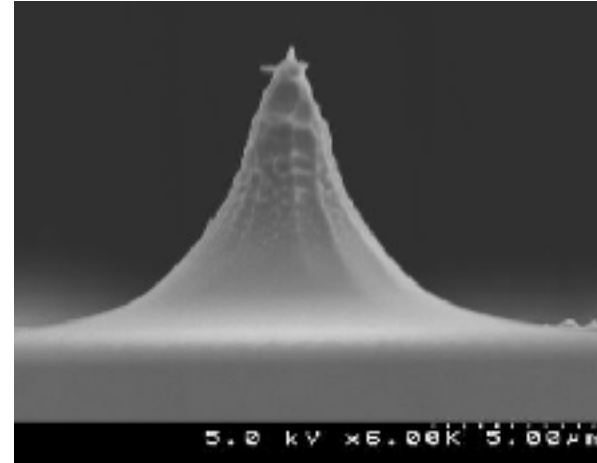
Si Tip after Plasma Etching



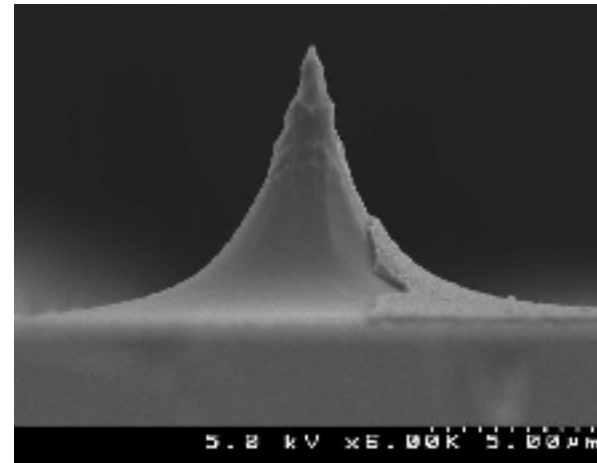
Si Tips before and after Oxidation Sharpening



(a) Before oxidation sharpening

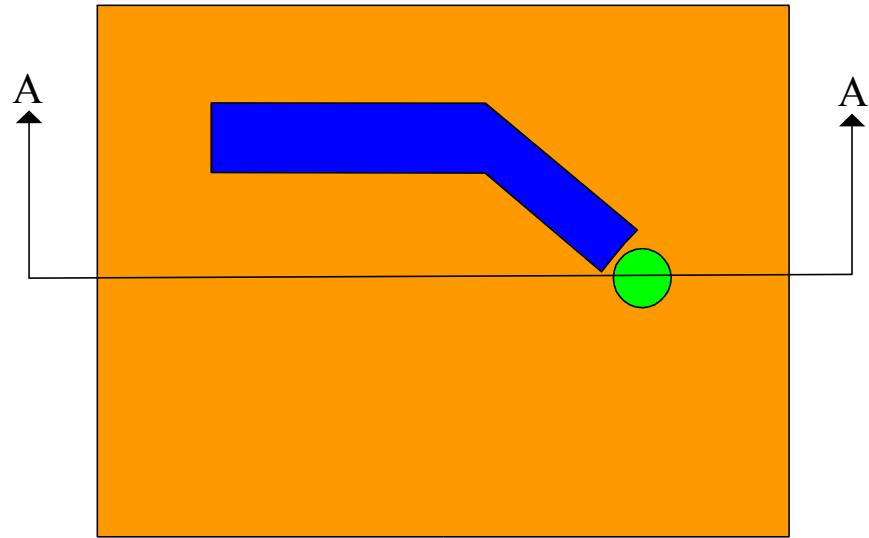


(b) After oxidation sharpening



Microfabrication: Waveguide

Metal deposition
Lithography
Metal etching



(c)



Si



Si



P+ diffusion



Thermal oxide

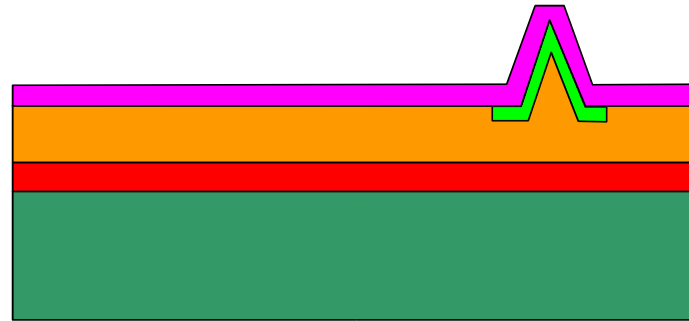


LTO



Al

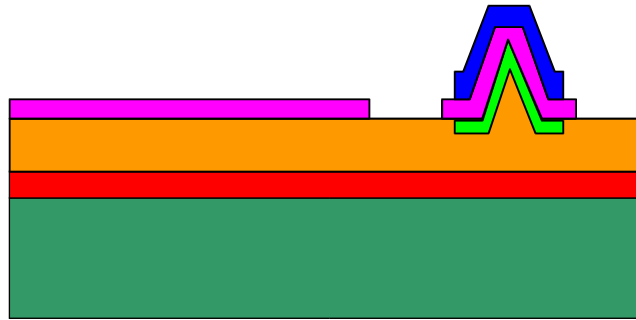
LTO deposition



(d)

Microfabrication: Shield Layer

Metal deposition
Lithography
Metal etching
Lithography
LTO etching



(e)



Si



Si



P+ diffusion



Thermal oxide

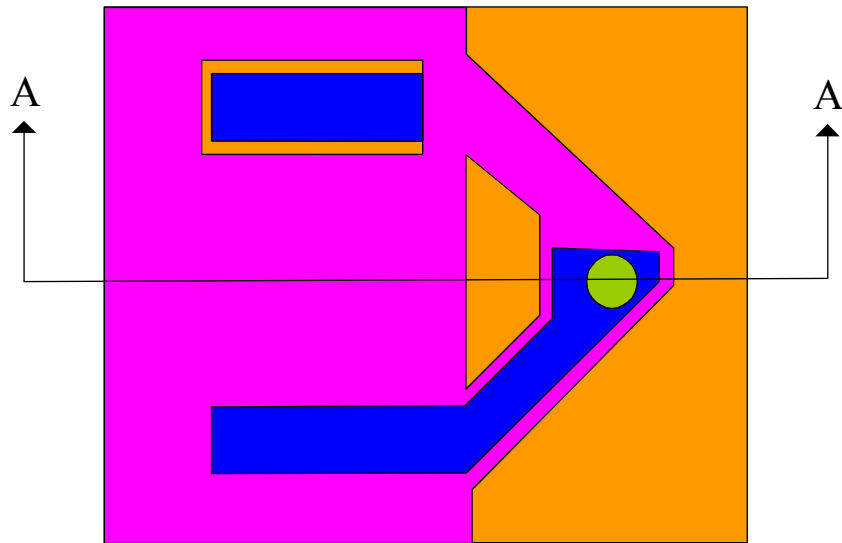


LTO



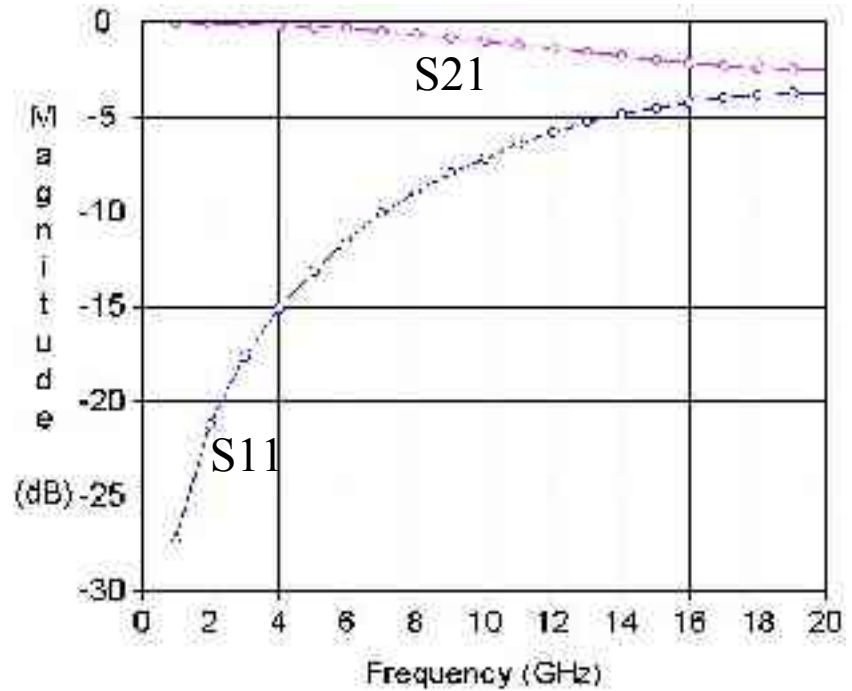
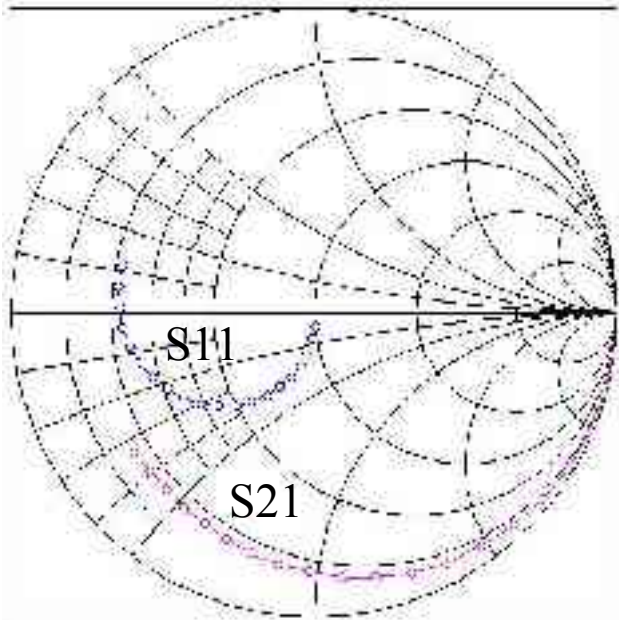
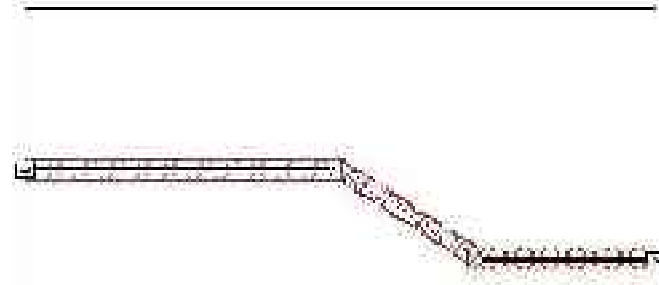
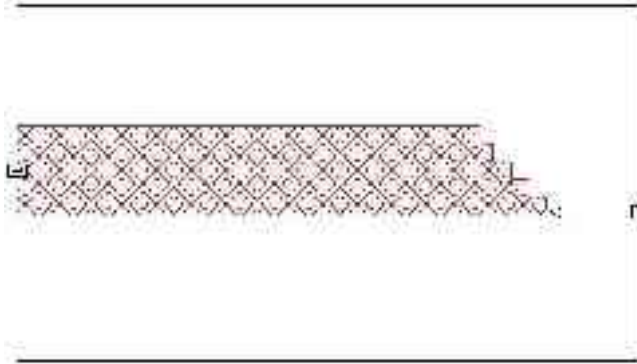
Al

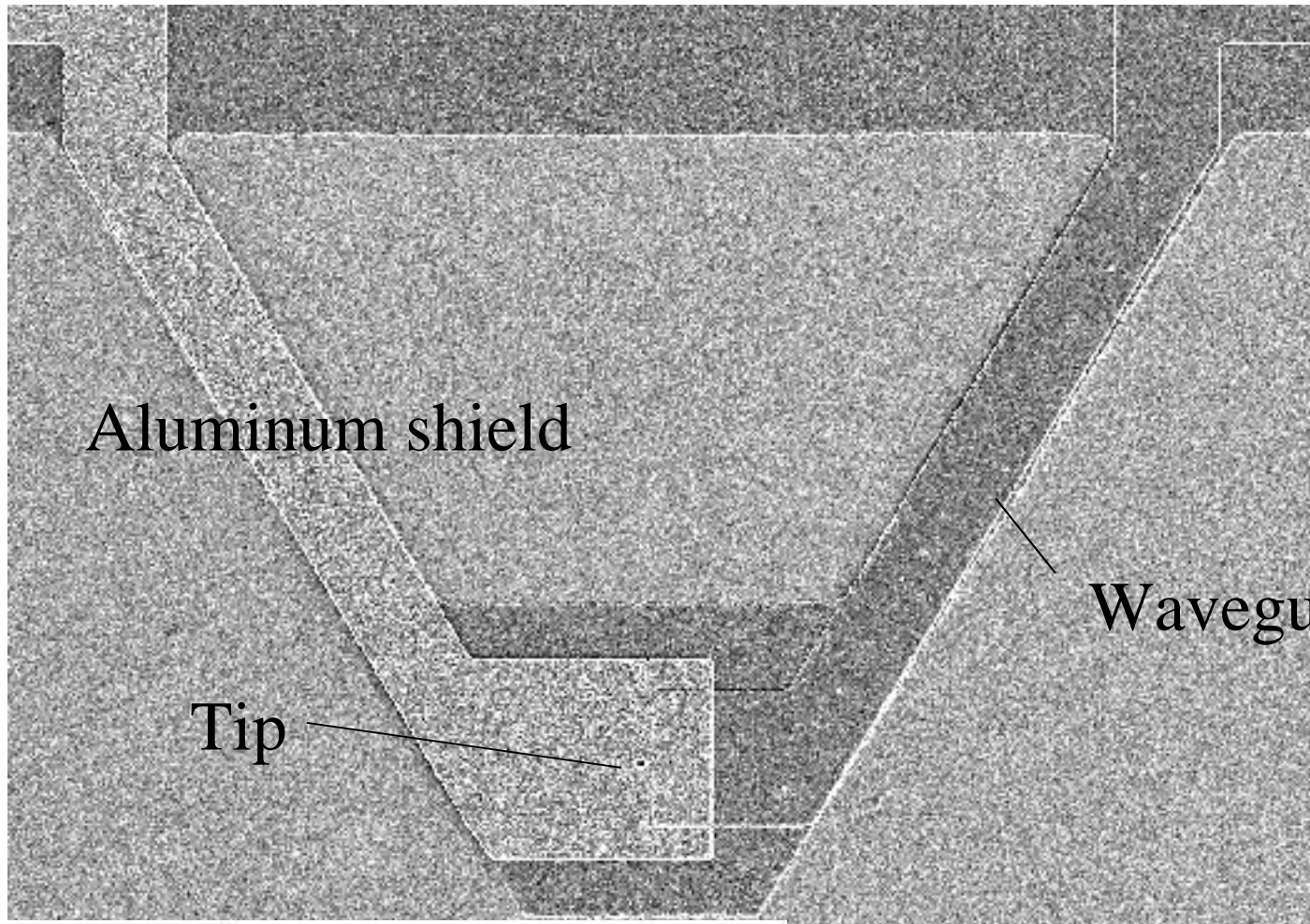
Top view
after step (e)



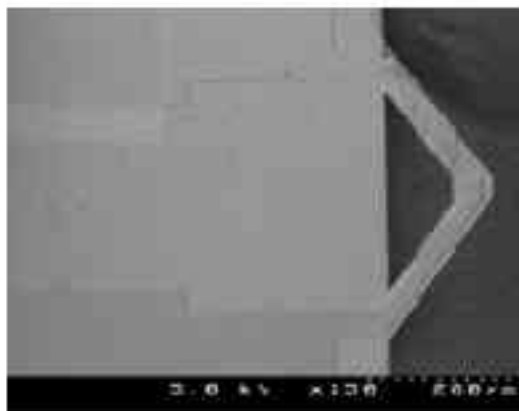
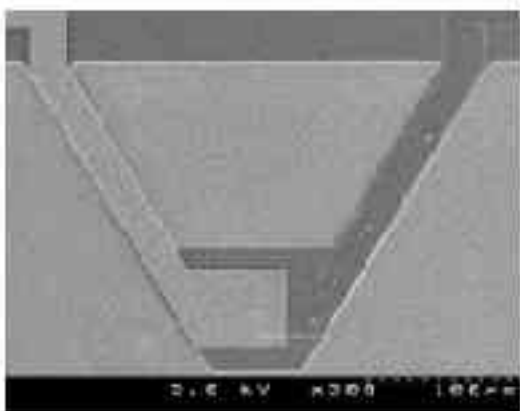
(f)

Microwave Design

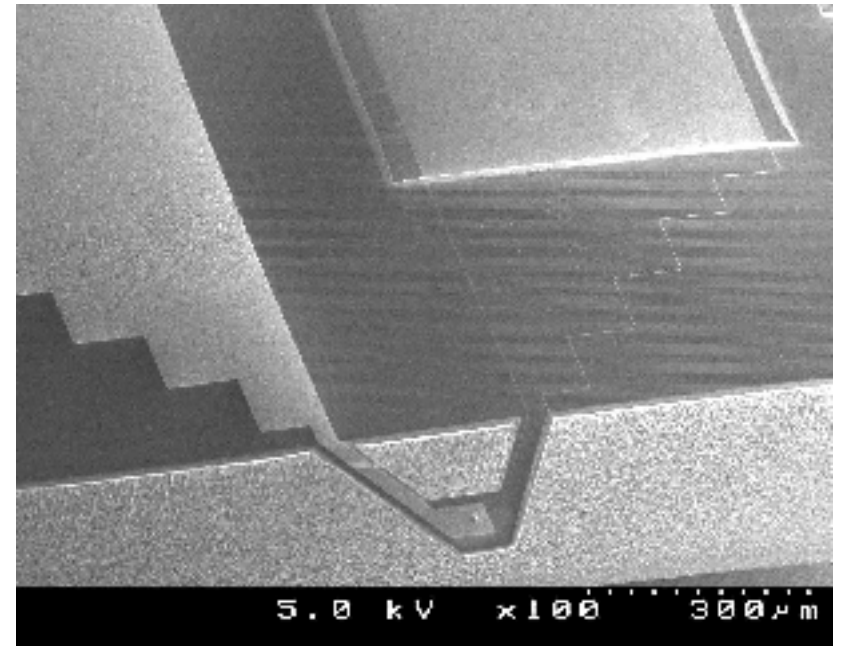
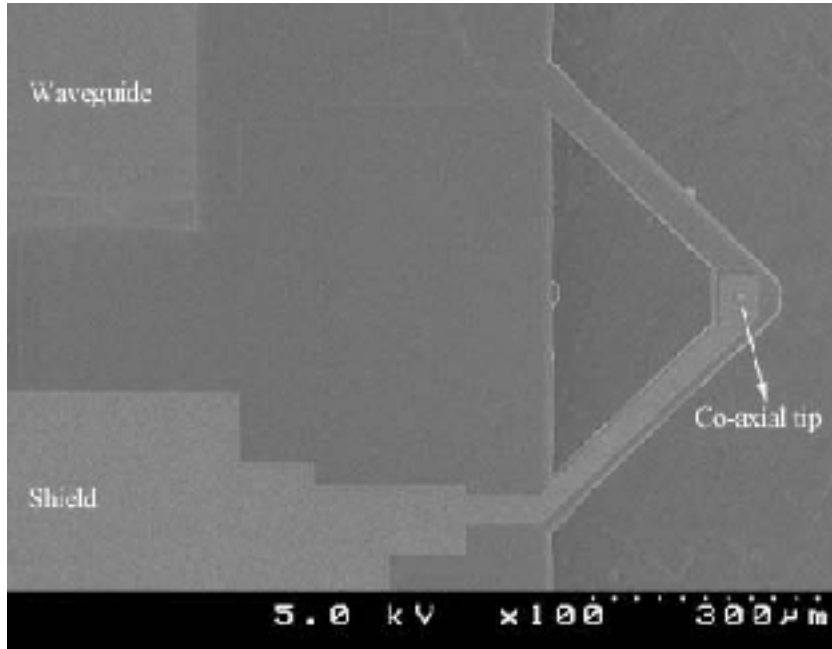




x300 100µm

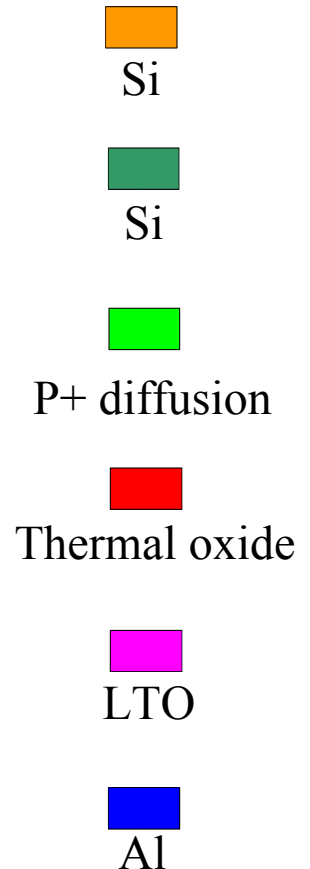
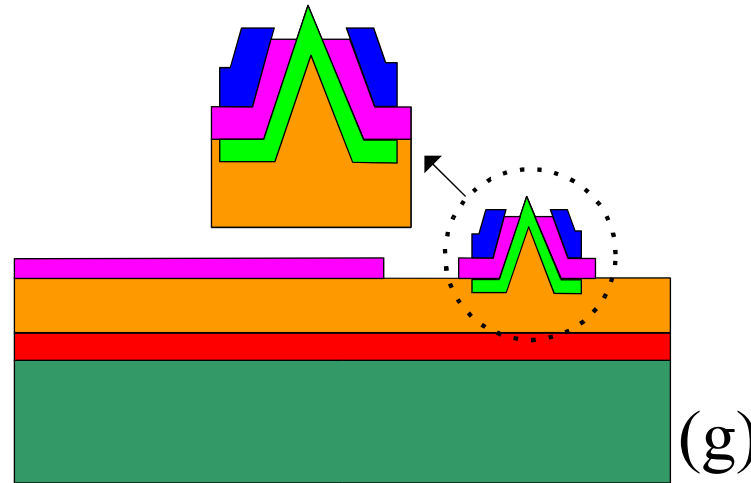


Released SNMM Probes

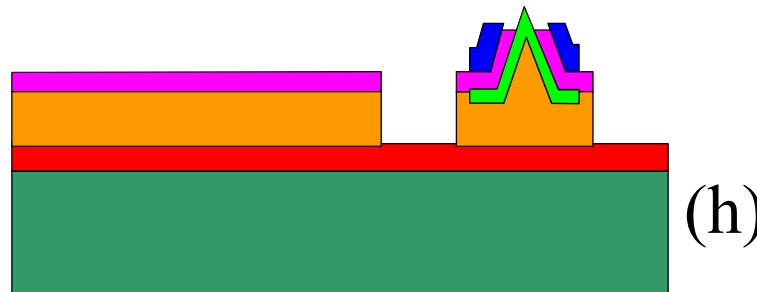


Microfabrication: Tip Exposure

PR coating
Tip exposure
Metal etching
LTO etching

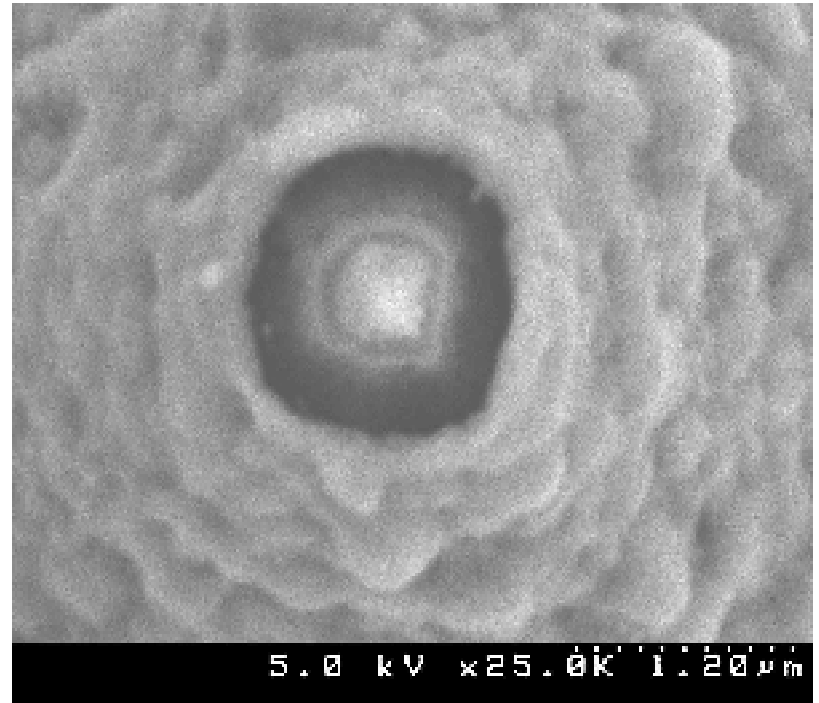
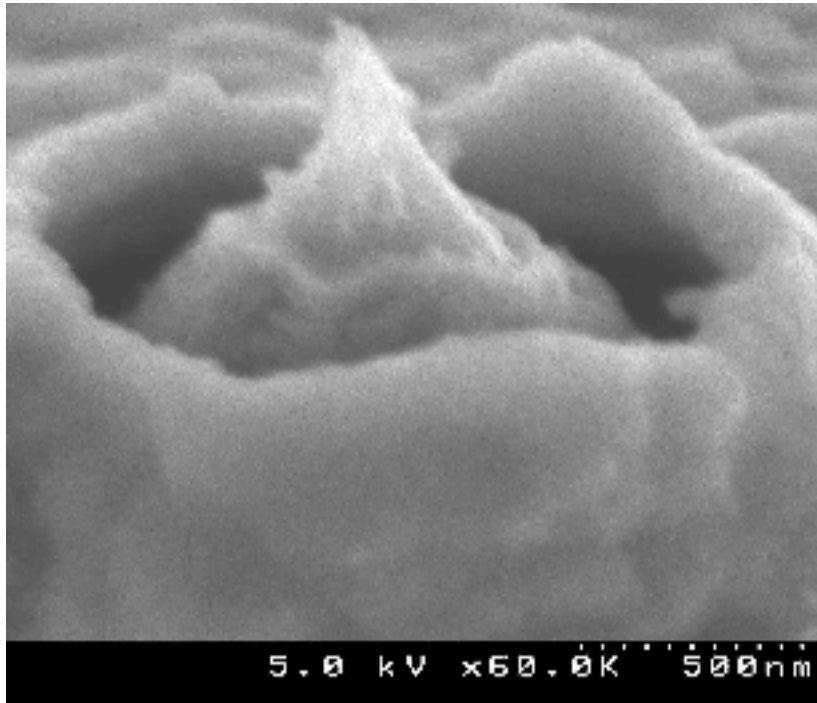


Lithography
Si RIE



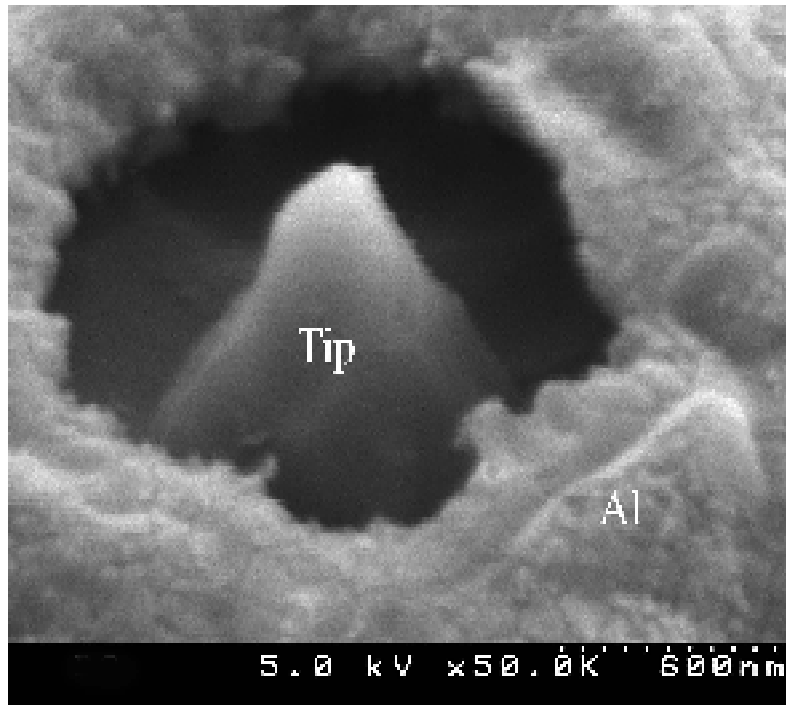
Y. Wang and M. Tabib-Azar, "Microfabricated Near-field Scanning Microwave Probes,"
Electron Devices Meeting, IEDM '02. Digest. International, IEEE, pp. 905-908 (2002).

Co-axially Shielded Tip (2)



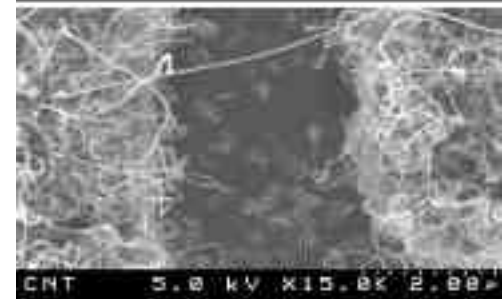
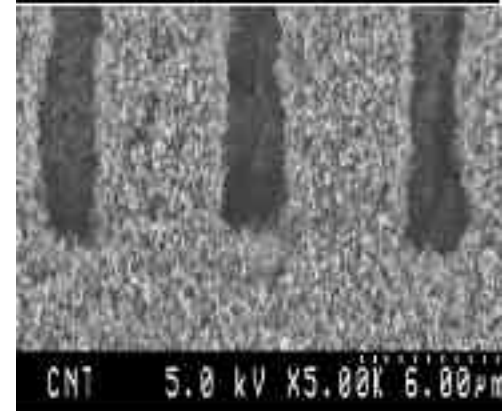
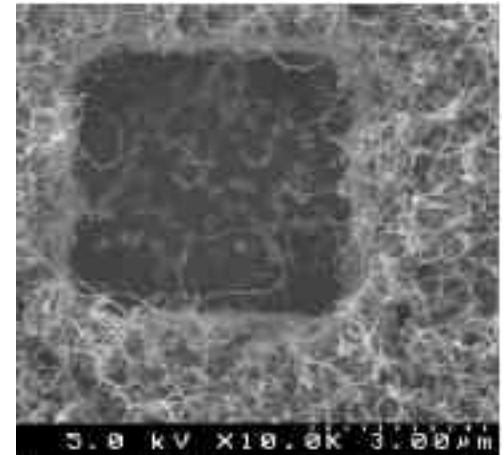
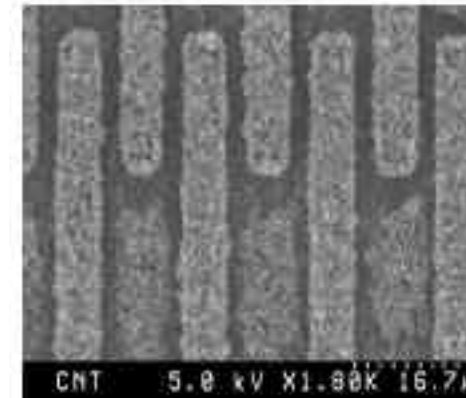
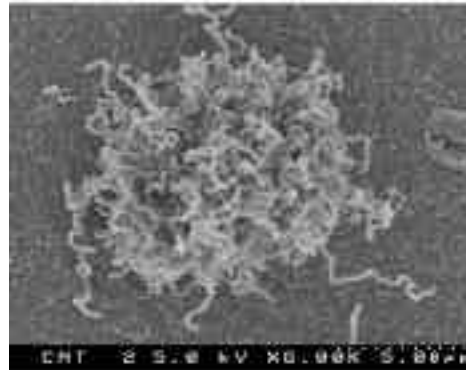
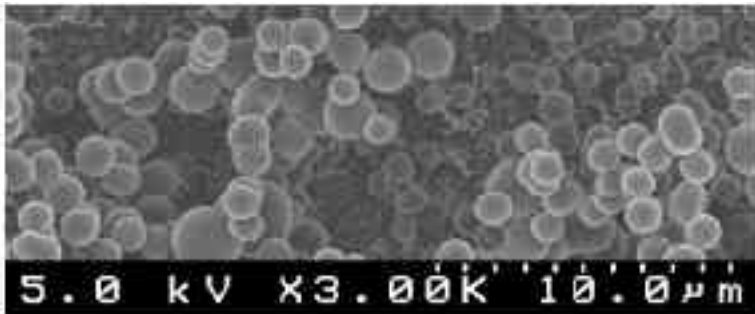
Y. Wang and M. Tabib-Azar, "Microfabricated Near-field Scanning Microwave Probes,"
Transducers '03

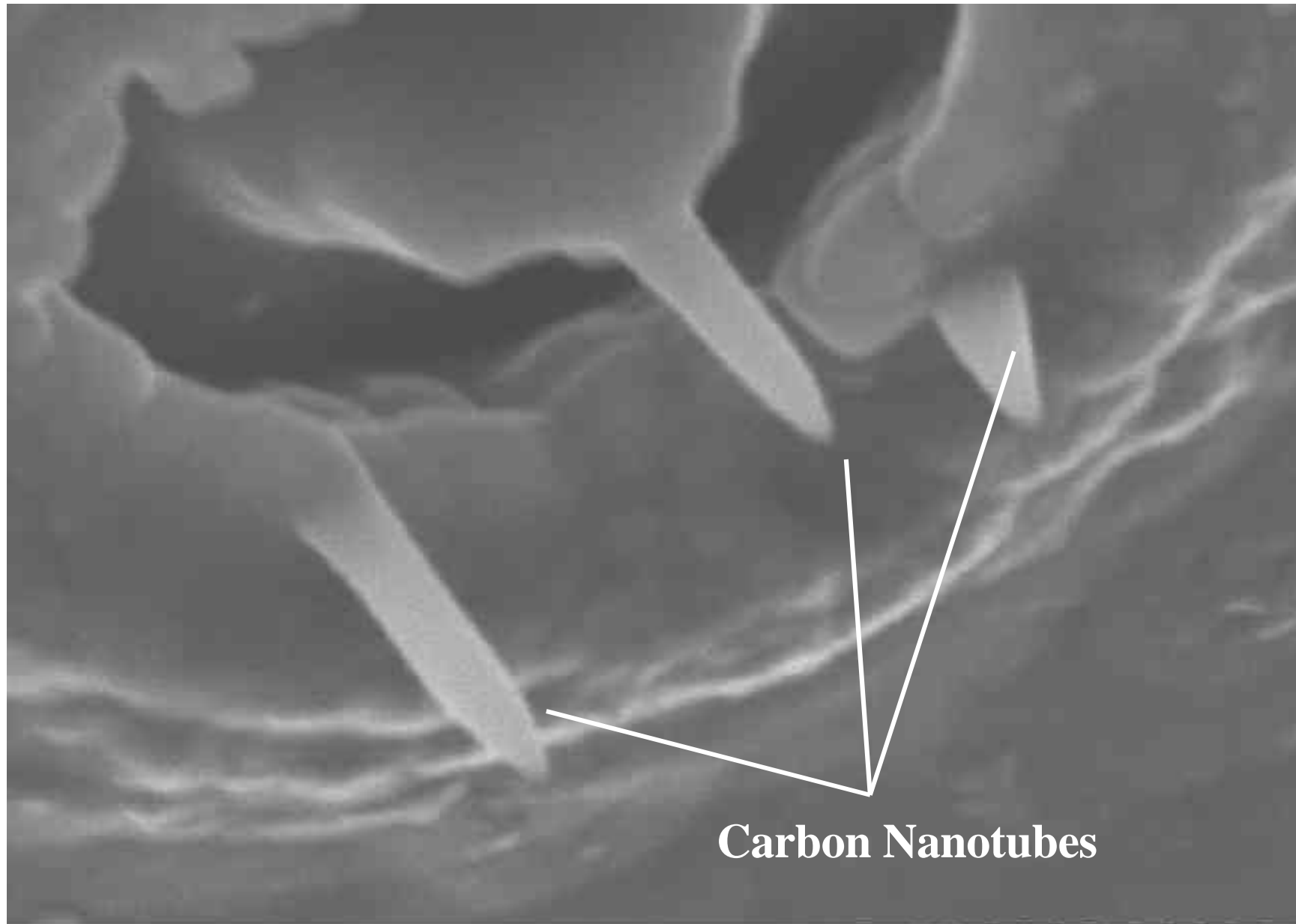
Coaxially shielded tip



Carbon Nanotubes & Nanospheres

Self-Assembled on Electrodes



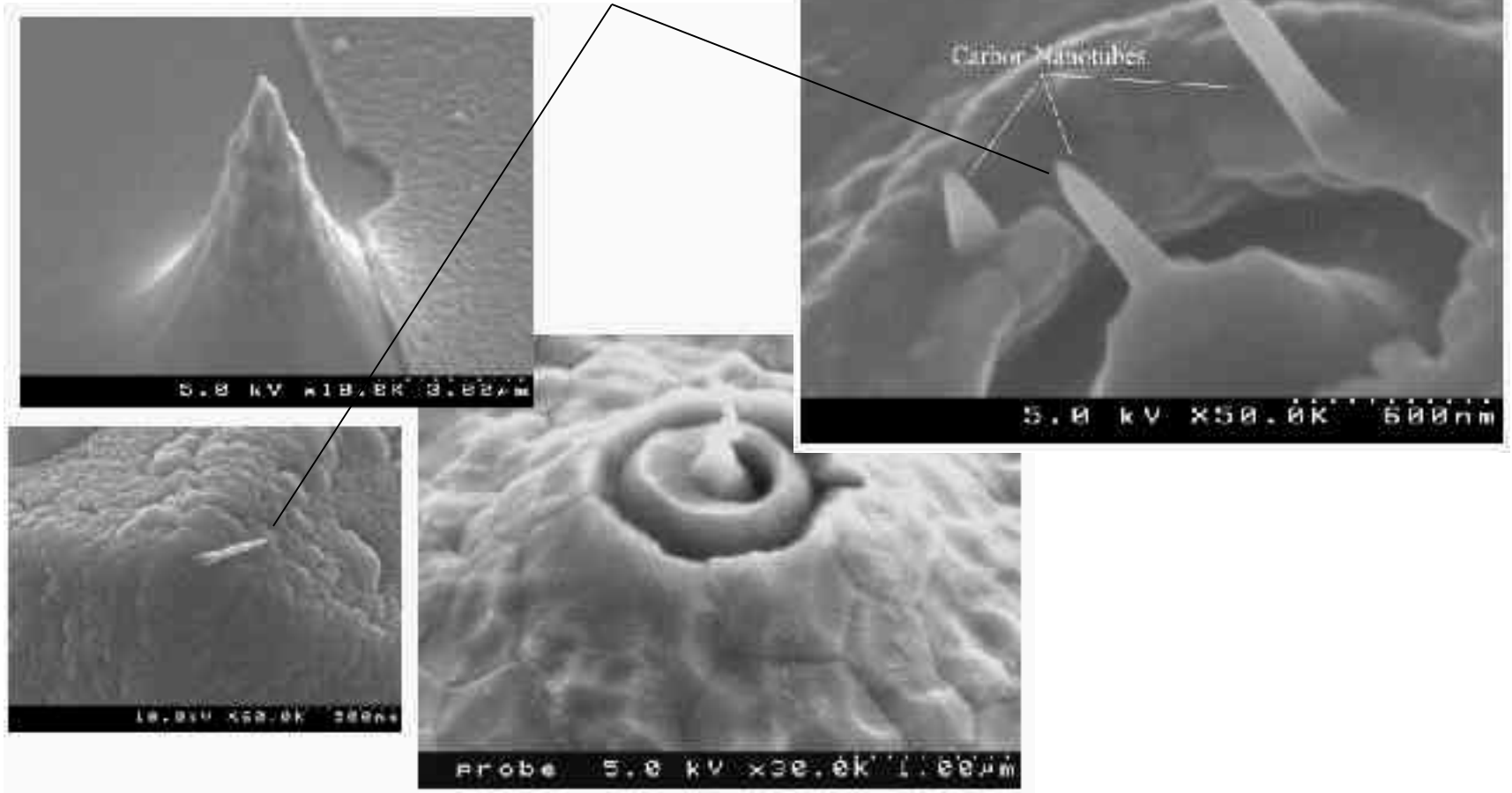


Carbon Nanotubes

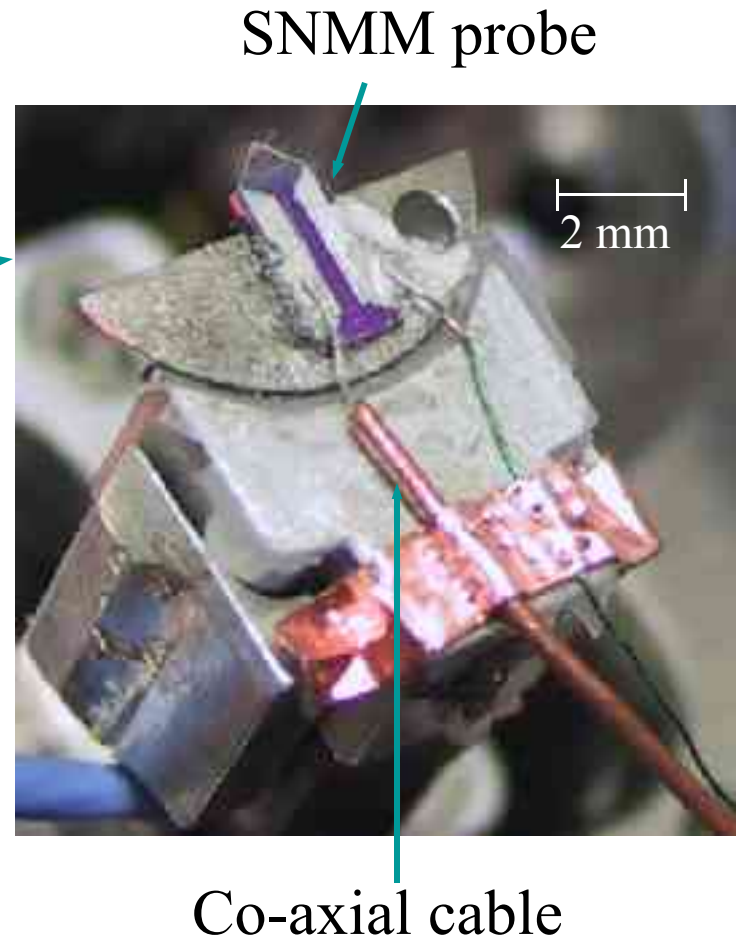
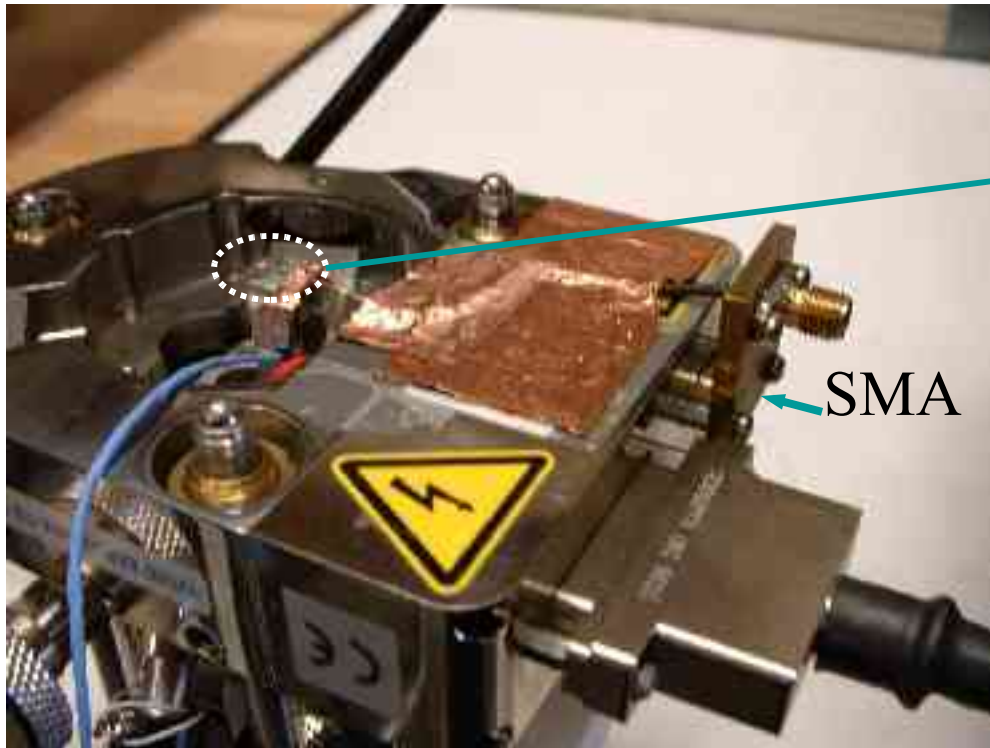
5.0 kV X50.0K 6000nm

Nano-Device Characterization

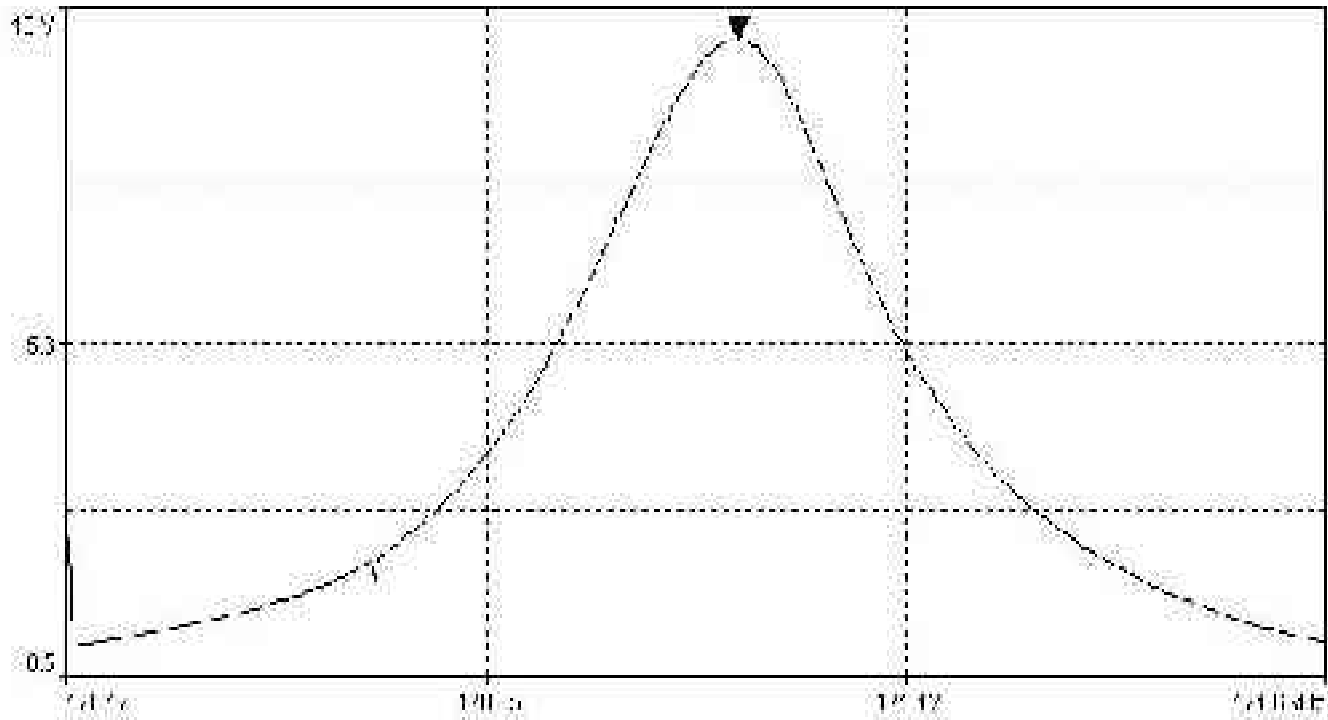
Carbon Nanotubes



AFM Head – Microwave Tip Assembly

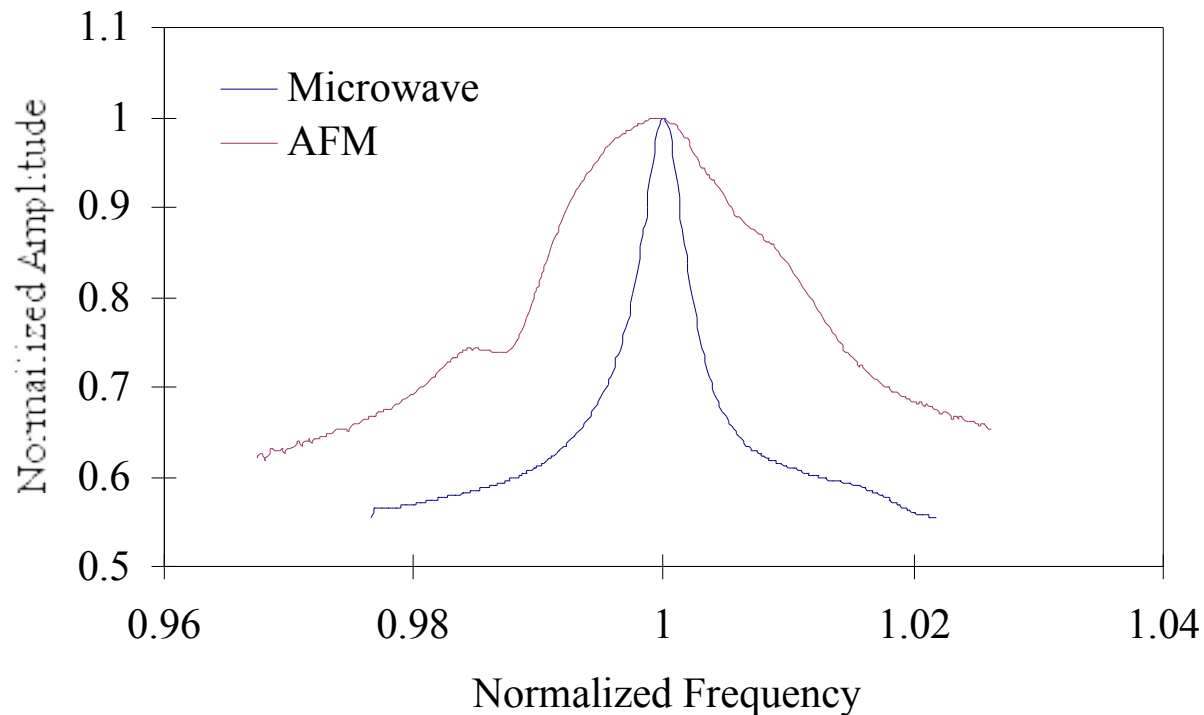


Mechanical Oscillation Spectrum



Measured resonant frequency is 170.92 KHz, and quality factor is 317. The design value is 150 KHz with $L = 300\mu\text{m}$, $W = 50\mu\text{m}$, and $t = 5\mu\text{m}$.

AFM-Compatible SEMP tip



Explorer™ AFM System

Scanner head

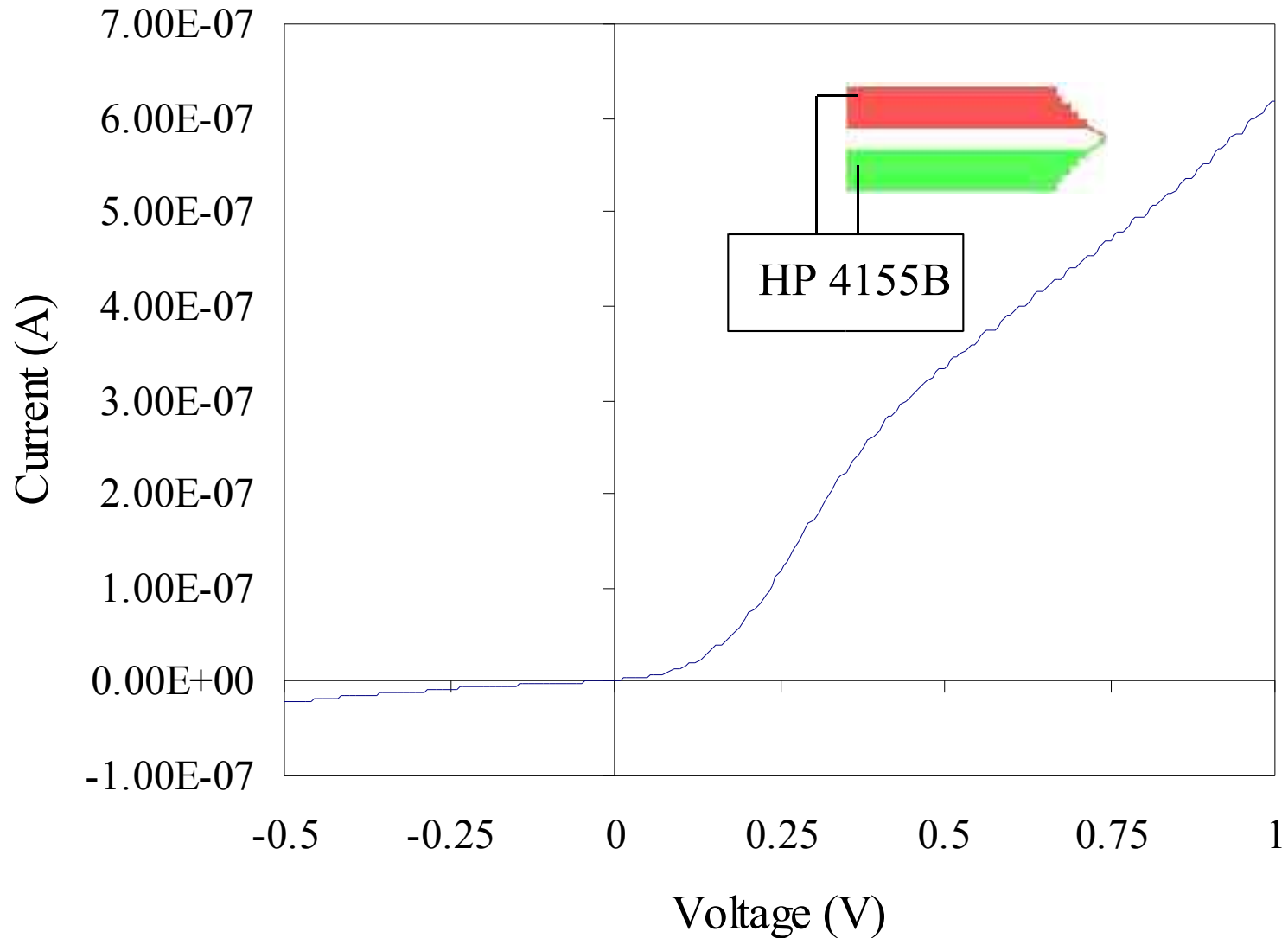


8 cm

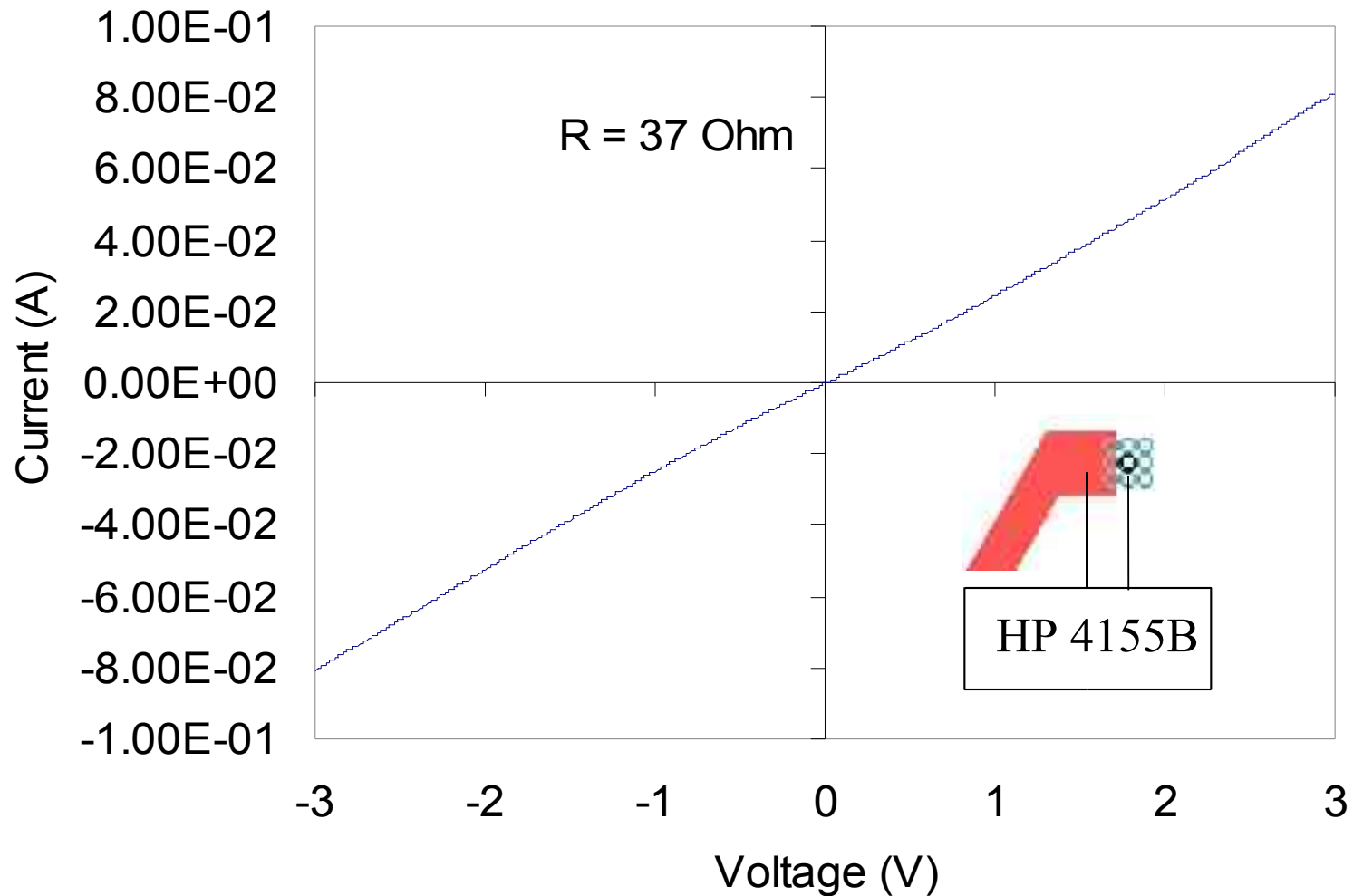
Sample holder



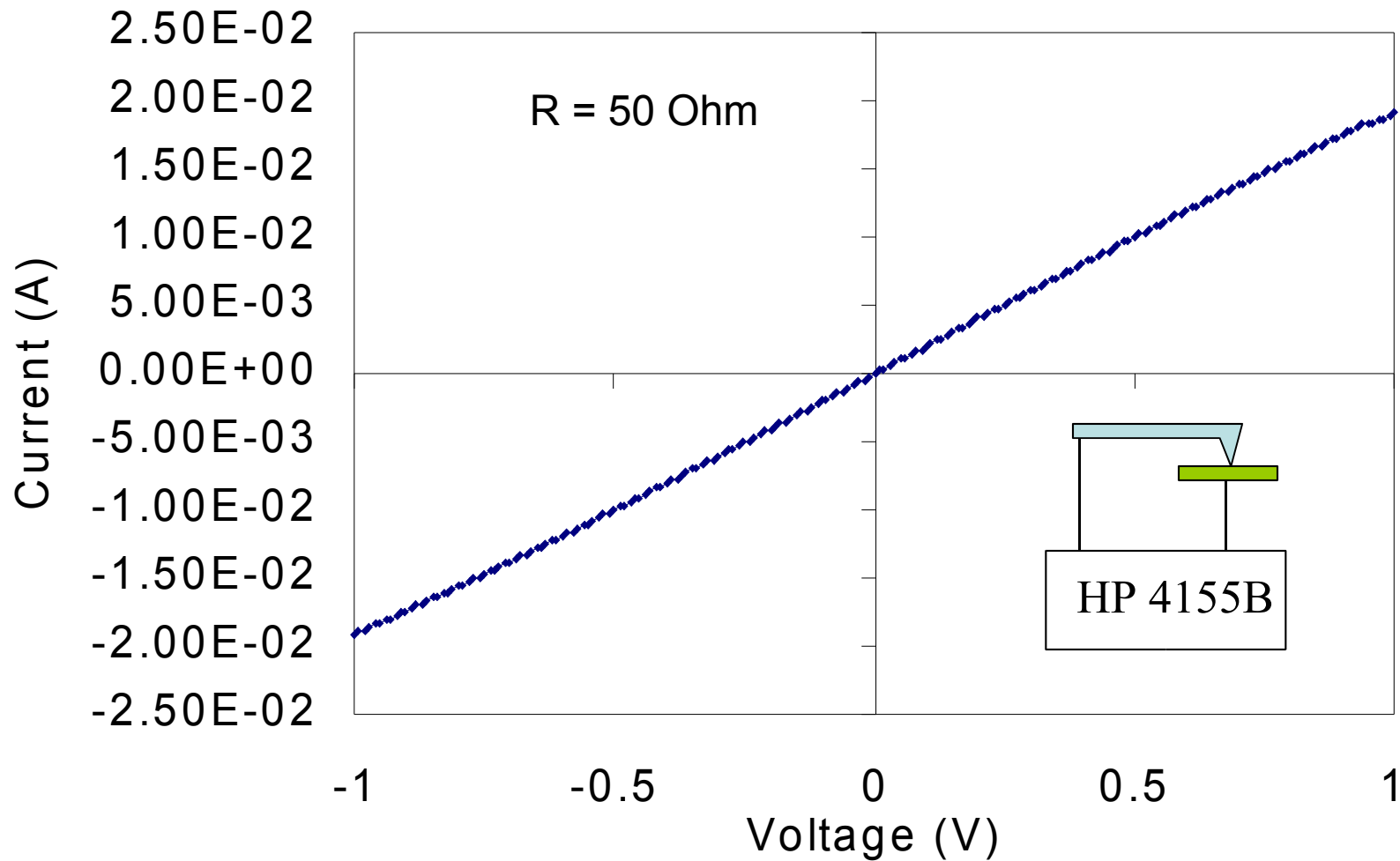
DC Conductivity between A Waveguide and A Shield



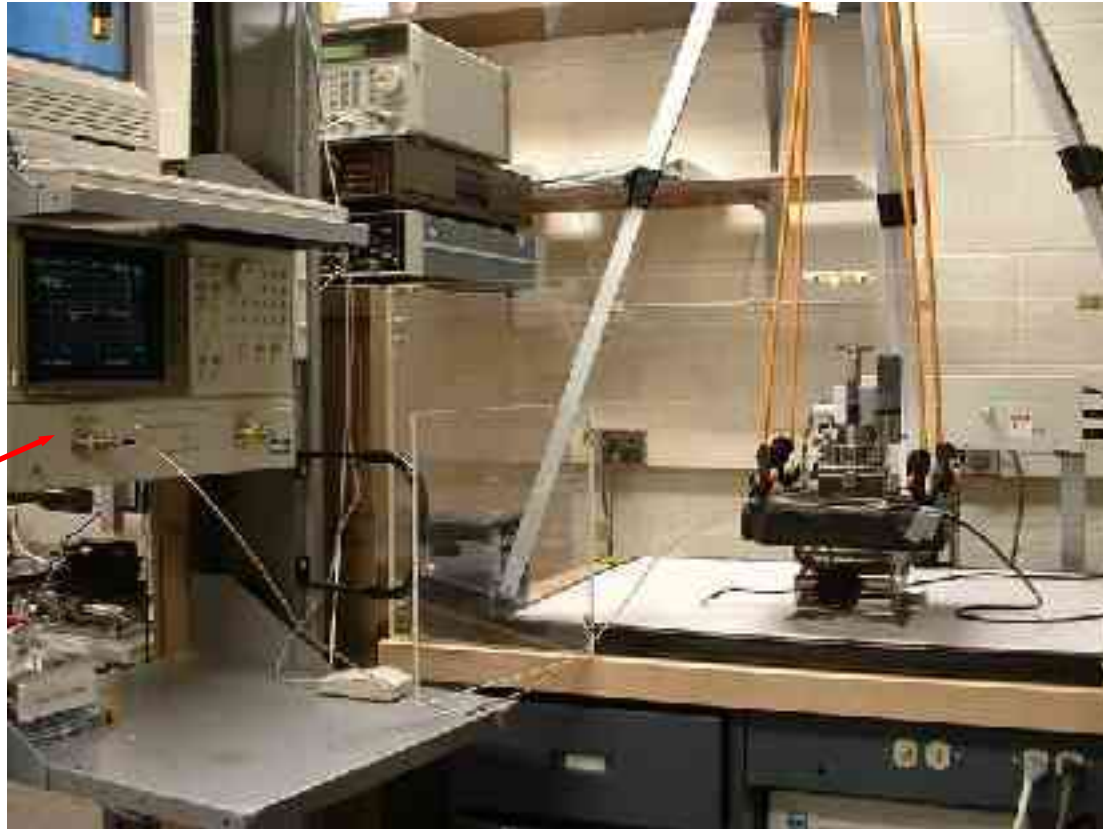
DC Conductivity between A Waveguide and An Implanted Tip Region



DC Conductivity between the Tip and An Au Sample

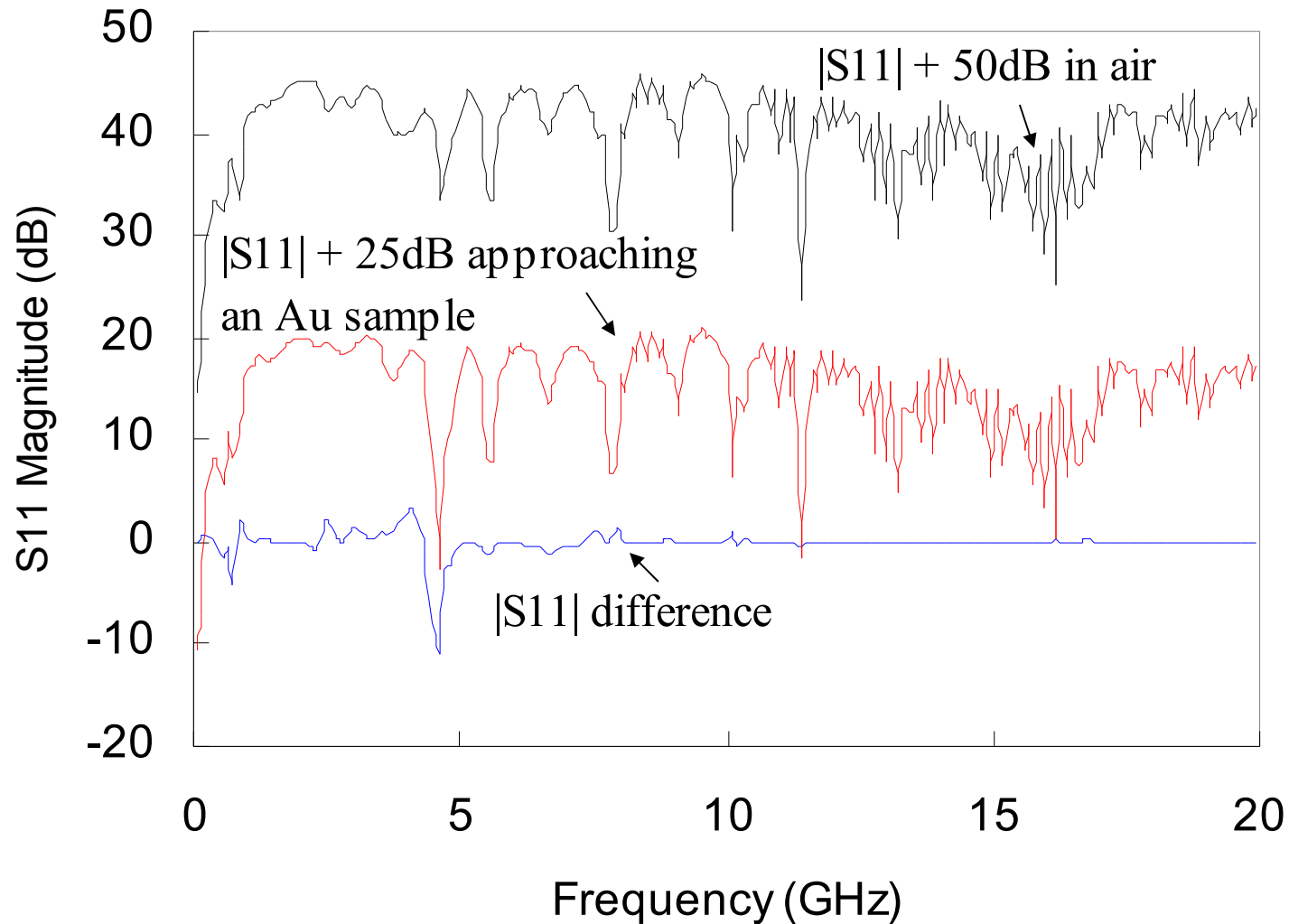


Microwave Measurement Setup

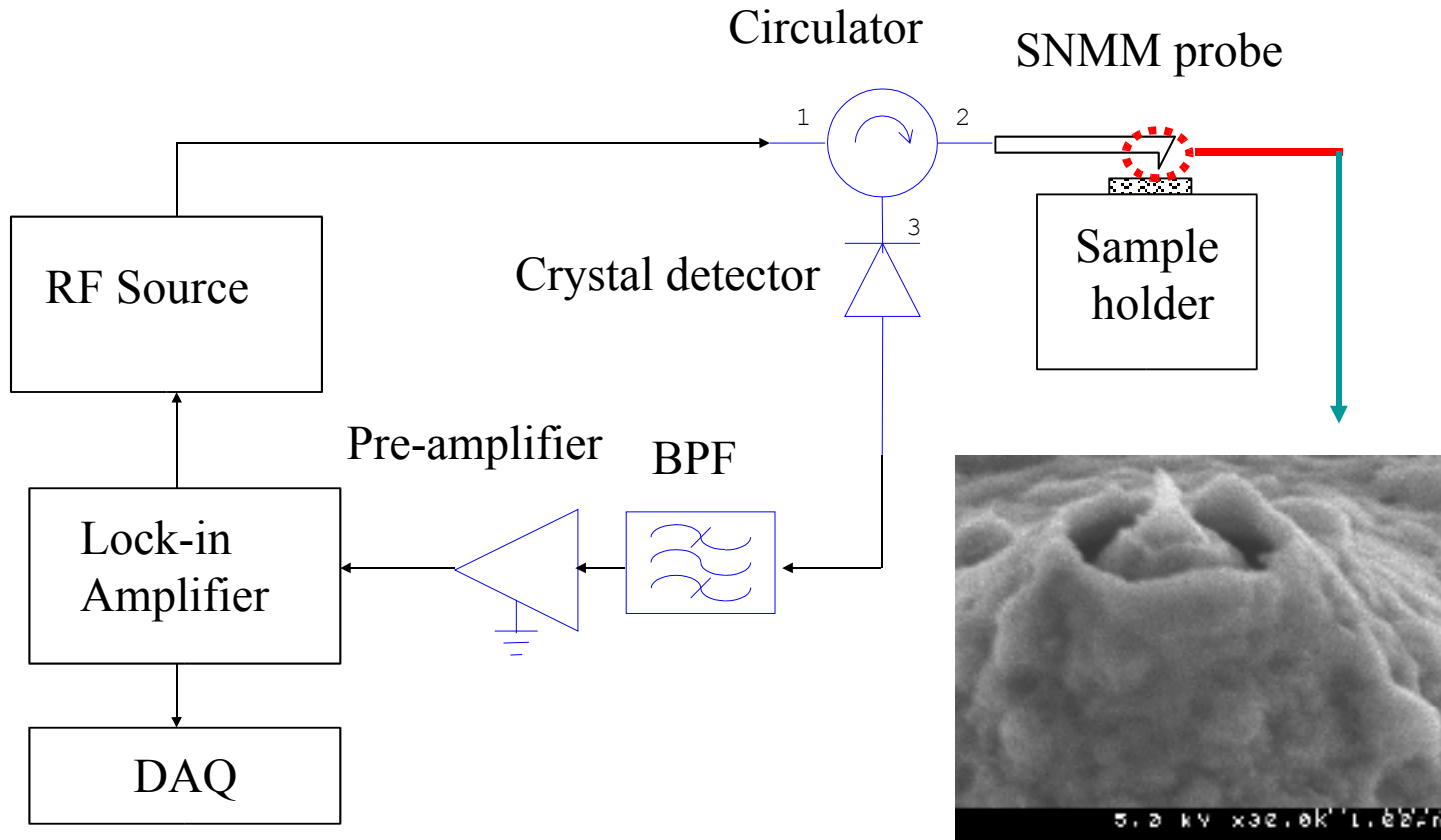


Network
Analyzer
HP 8720C

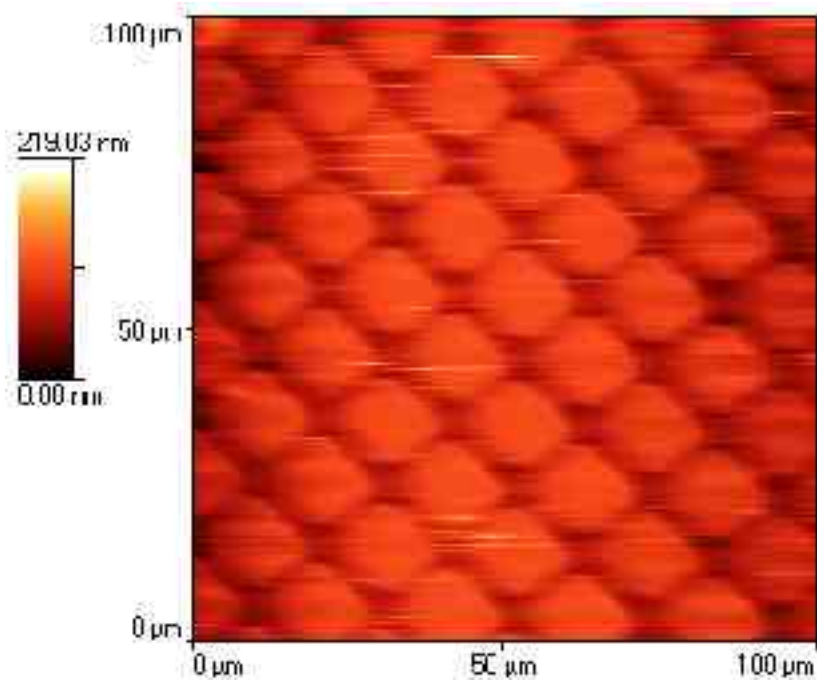
S11 Measurements in Air and over An Au Sample



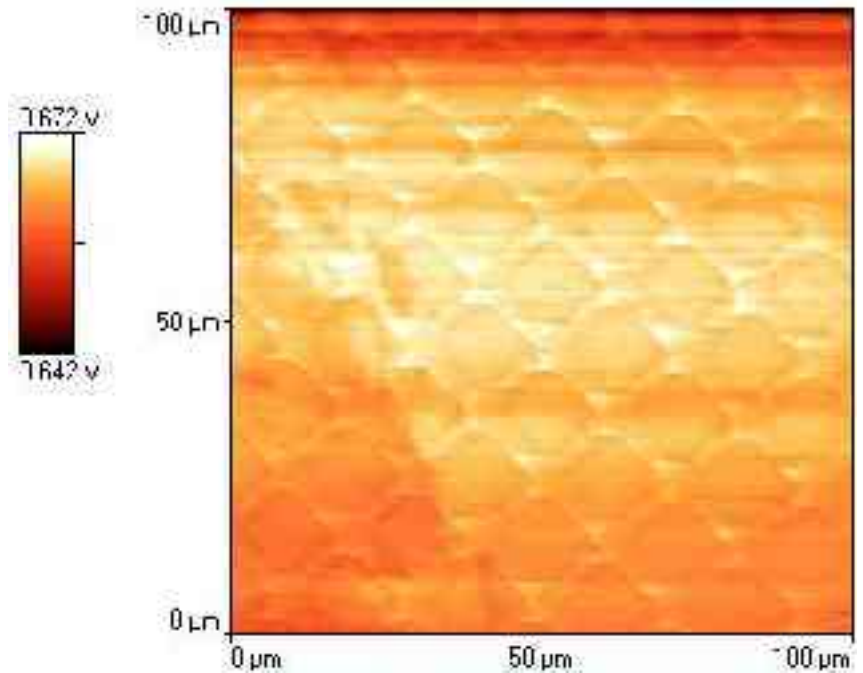
Schematic of the Image Scanning Circuit



Simultaneous AFM and Scanning Near-field Microwave Images (2.8 GHz)

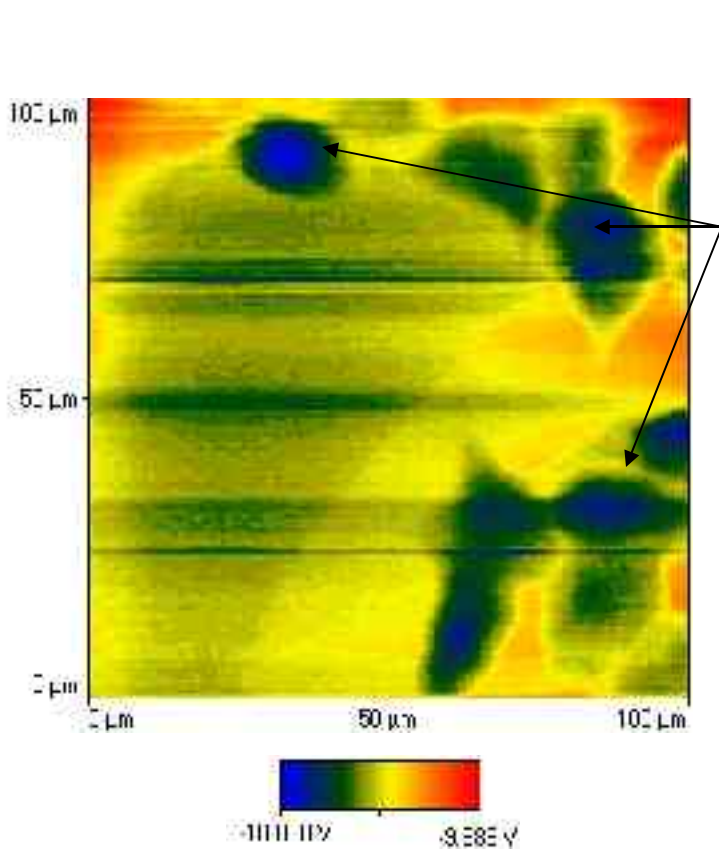


Contact AFM



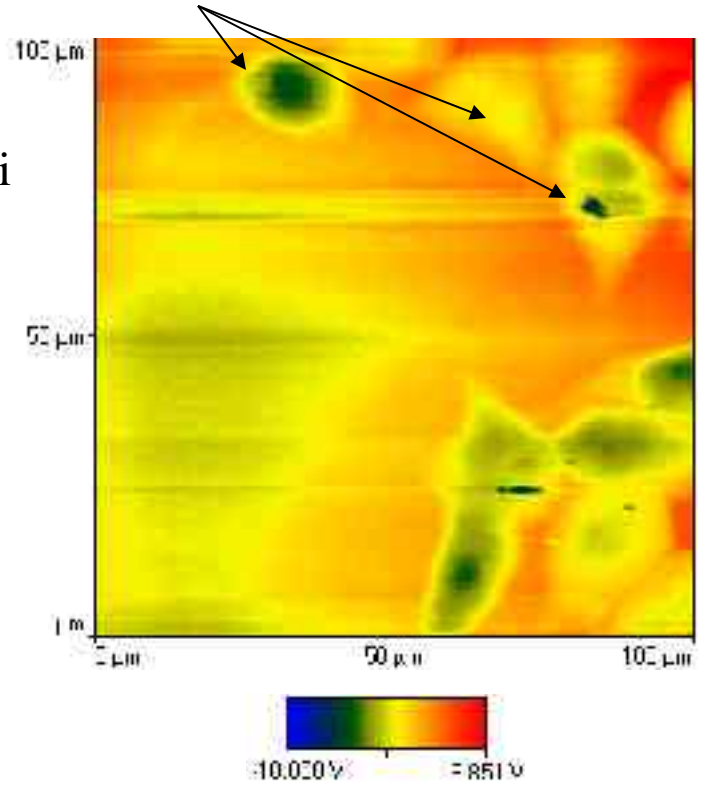
Microwave Image

Use microwave AFM to see inside the cell



Cell nuclei

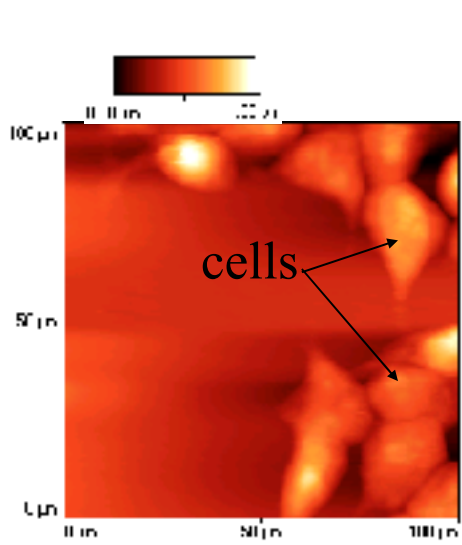
Membrane contrasted



Microwave AFM amplitude

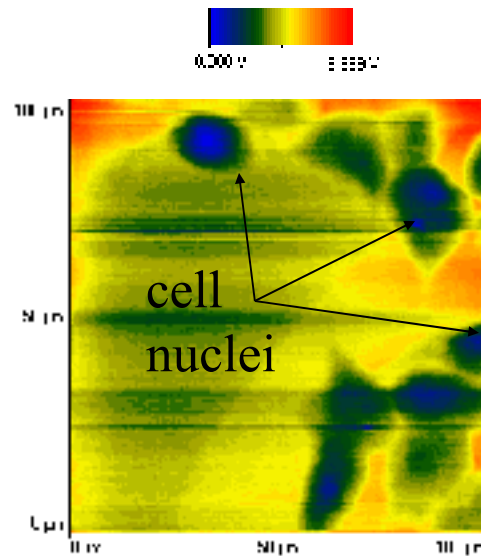
Microwave AFM phase

Significance of Scanning Near-field Microwave Microscope (1.8 GHz)



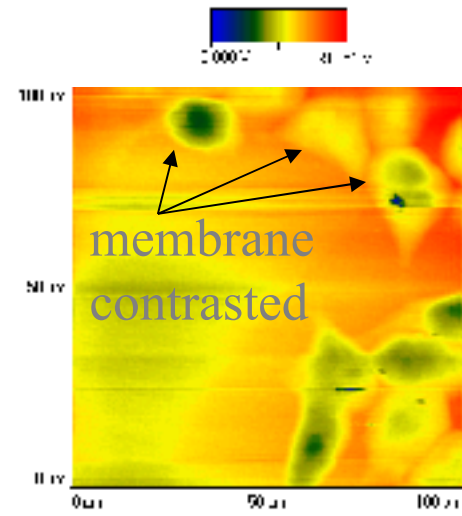
(a)

AFM topography



(b)

SNMM amplitude

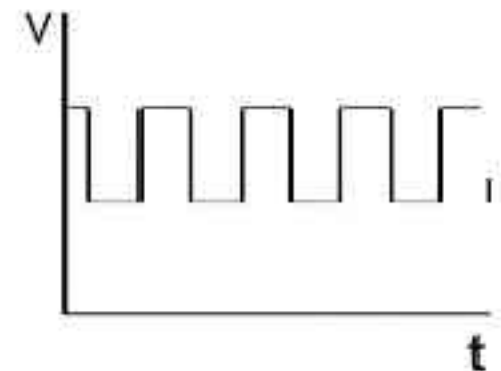
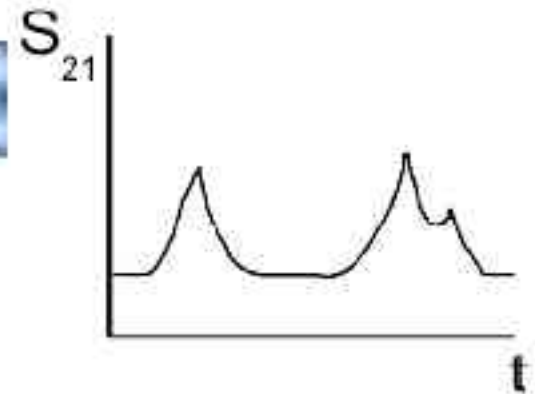
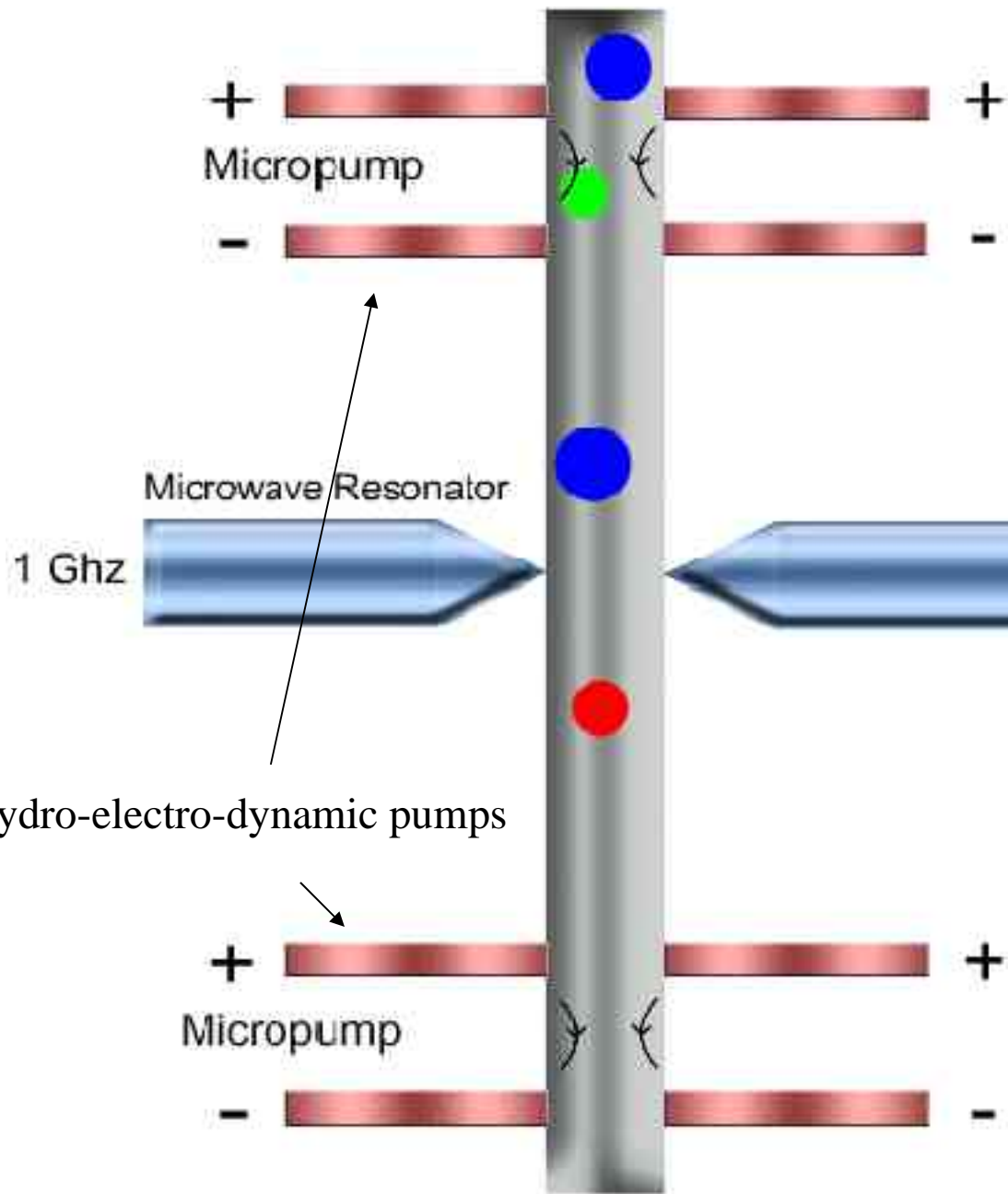


(c)

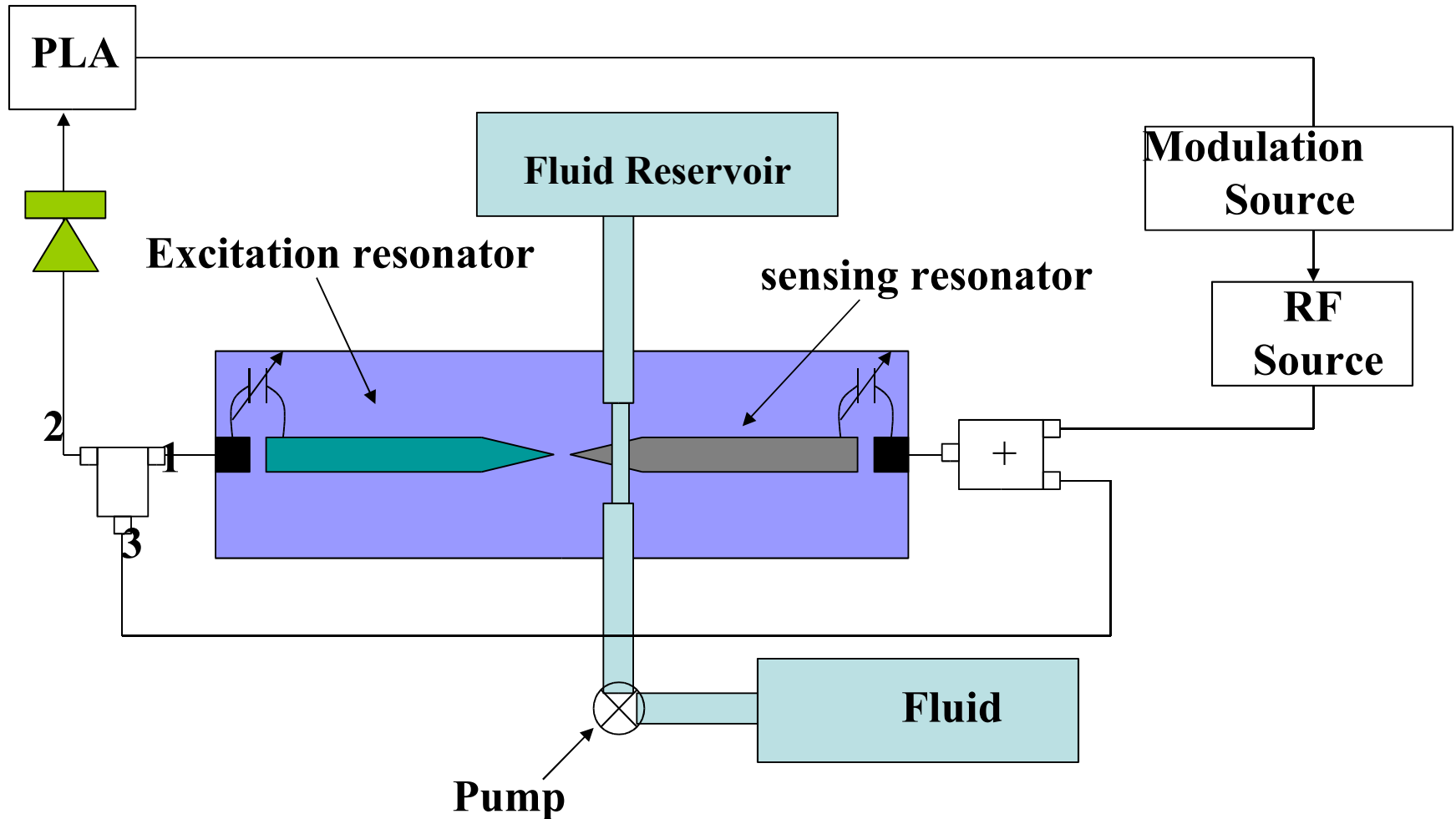
SNMM phase

Commonly used

Microwave Microscopy Of Molecules in Micro- Fluidics



Micro-Fluidic: Experimental Arrangement



Detection of Cavitation bubbles using SEMP

<0.1 μm Bubbles

